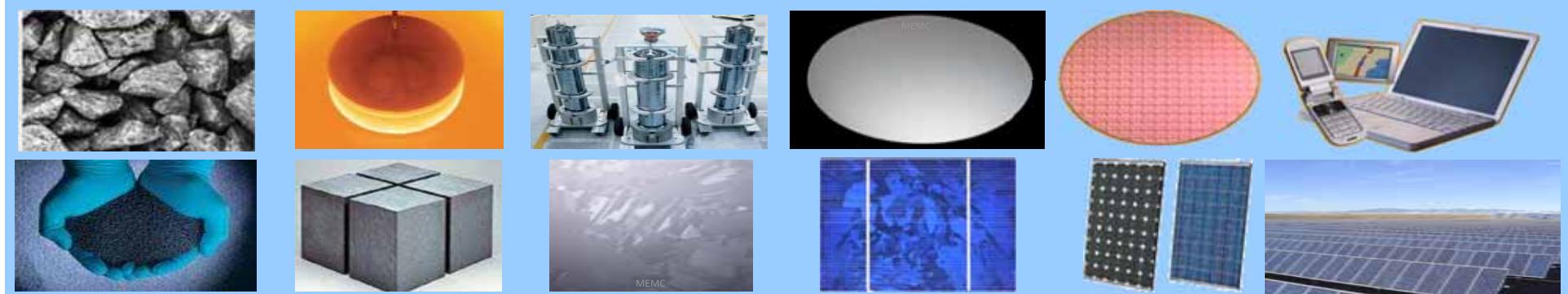


*Exceptional service in the national interest*



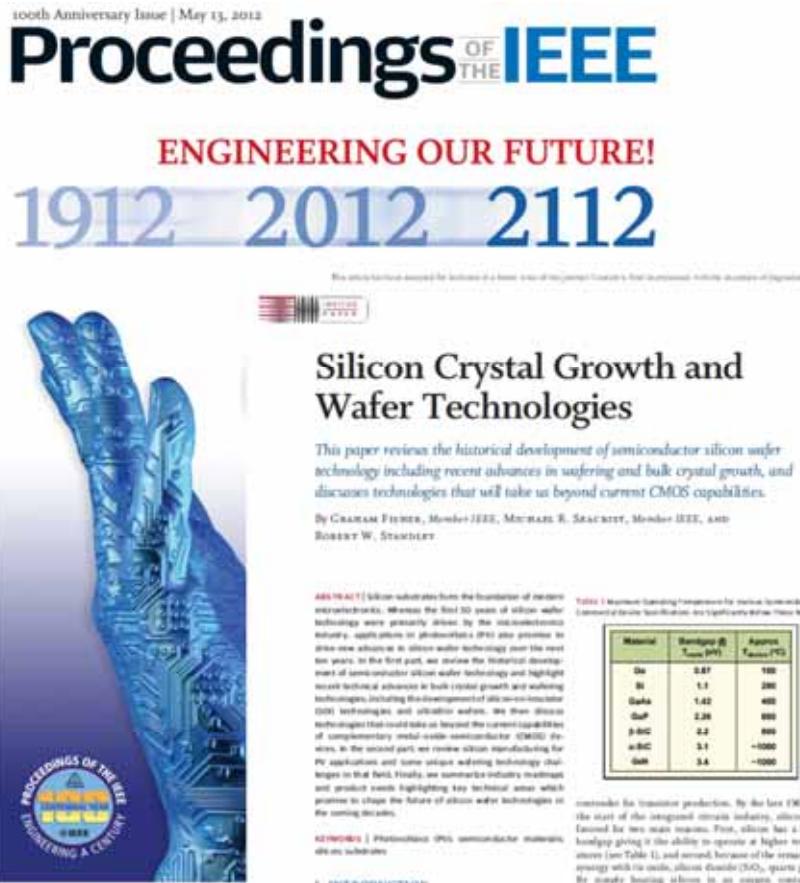
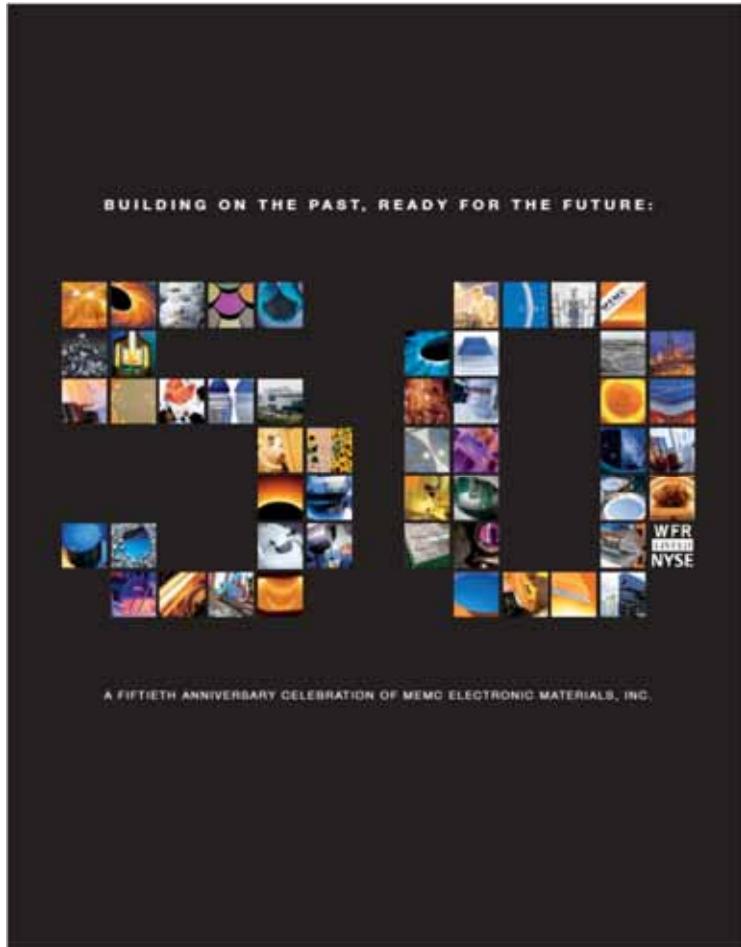
## Manufacturing of Silicon Materials for Microelectronics and Solar PV

Babu Chalamala, Ph.D.



Sandia National Laboratories is a multi-mission laboratory managed and operated by National Technology and Engineering Solutions of Sandia, LLC, a wholly owned subsidiary of Honeywell International, Inc., for the U.S. Department of Energy's National Nuclear Security Administration under contract DE-NA0003525  
SAND No:

# Background Material



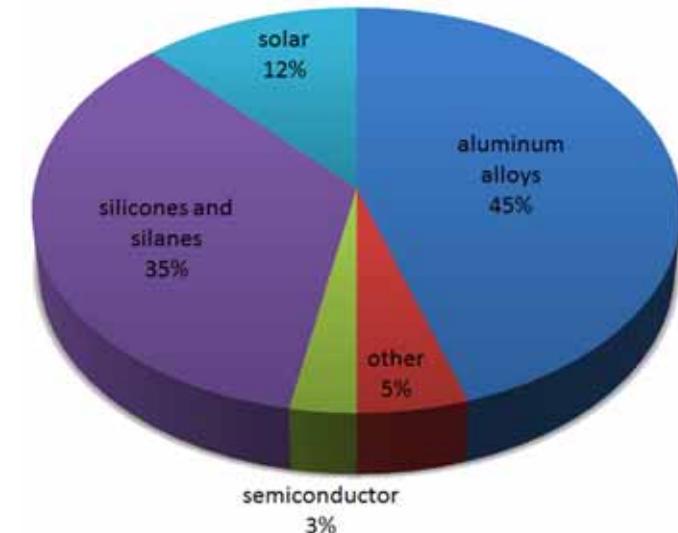
[http://www.memc.com/assets/file/company/MEMC\\_book-optimized.pdf](http://www.memc.com/assets/file/company/MEMC_book-optimized.pdf)

<http://ieeexplore.ieee.org/xpl/tocresult.jsp?isnumber=6259910&punumber=5>

# Silicon as an Industrial Material



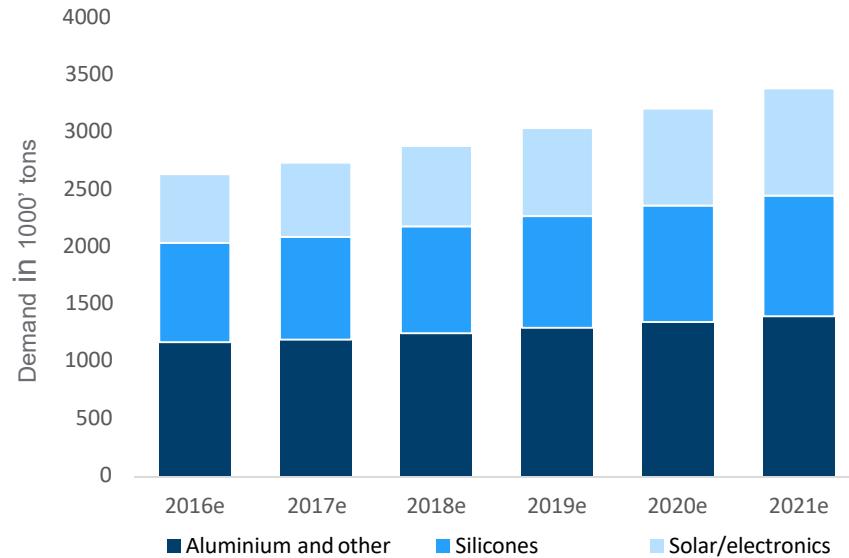
Silicon Metal			
			
Composition	99% Silicon		
Main Market	Aluminum	Silicones	Semiconductors
Usage	Silicon source	Feedstock	Bulk Material



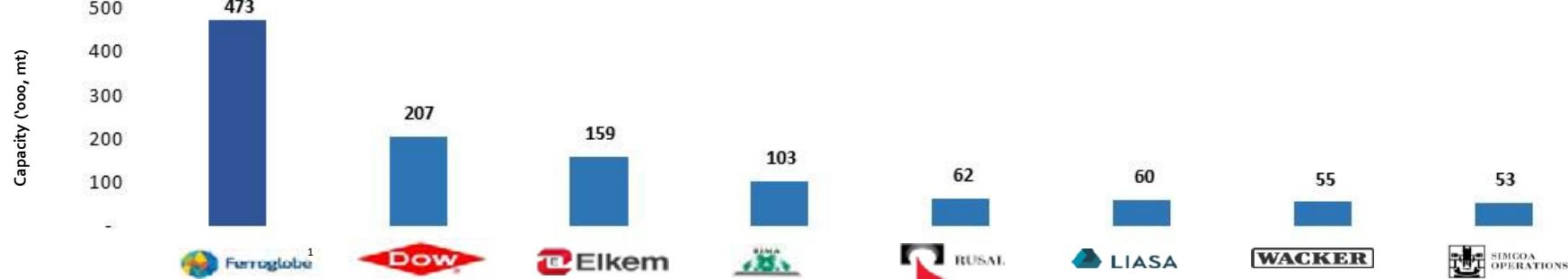
CRU Market Data, 2017

- Out of the 2.5 million of tons of silicon metal produced, about 300k tons goes into producing wafers for solar and microelectronics
- Metallurgical and chemical applications consume over 80% of Si produced

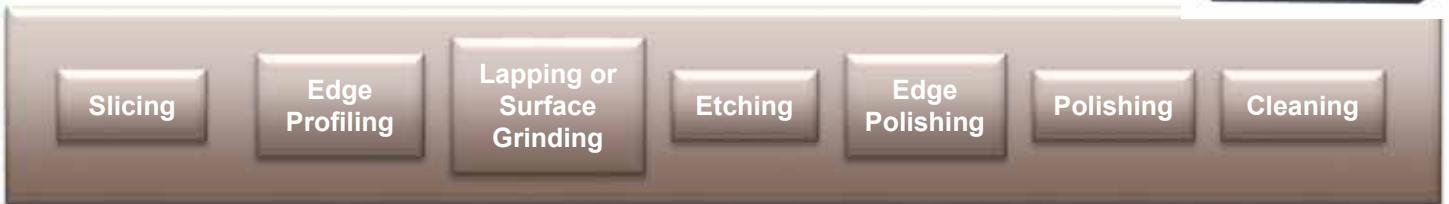
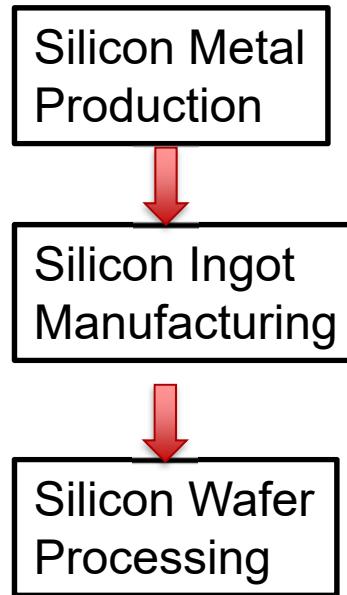
# Silicon Materials Market



- With raising demand for Si in PV, both demand and production continues to grow.



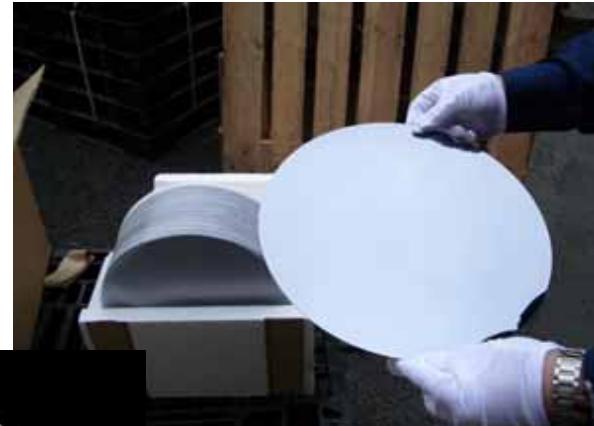
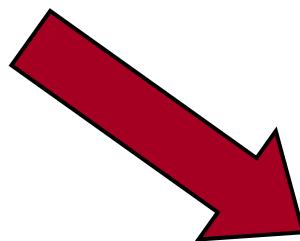
# From Quartz to Silicon Wafers



# How Do We Make Silicon?



*How do we go from quartz ...  
... to make silicon?*



# Silicon Metal Production



**PRODUCT:** Metallurgical      Chemical      Polysilicon

**MAIN MARKET:** Aluminum      Silicones      Solar

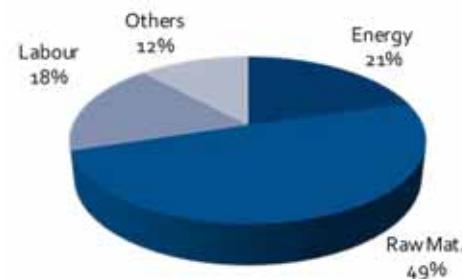
**TYPICAL  
COMPOSITION:** 99% Silicon

**MAIN CHEMICAL  
REACTION:**  $\text{SiO}_2 \rightarrow \text{Si}$

**ORE:** High purity quartz

**CARBON SOURCE:** Low ash coal, charcoal, wood

**ENERGY REQUIRED  
(kWh/t)** 12,000

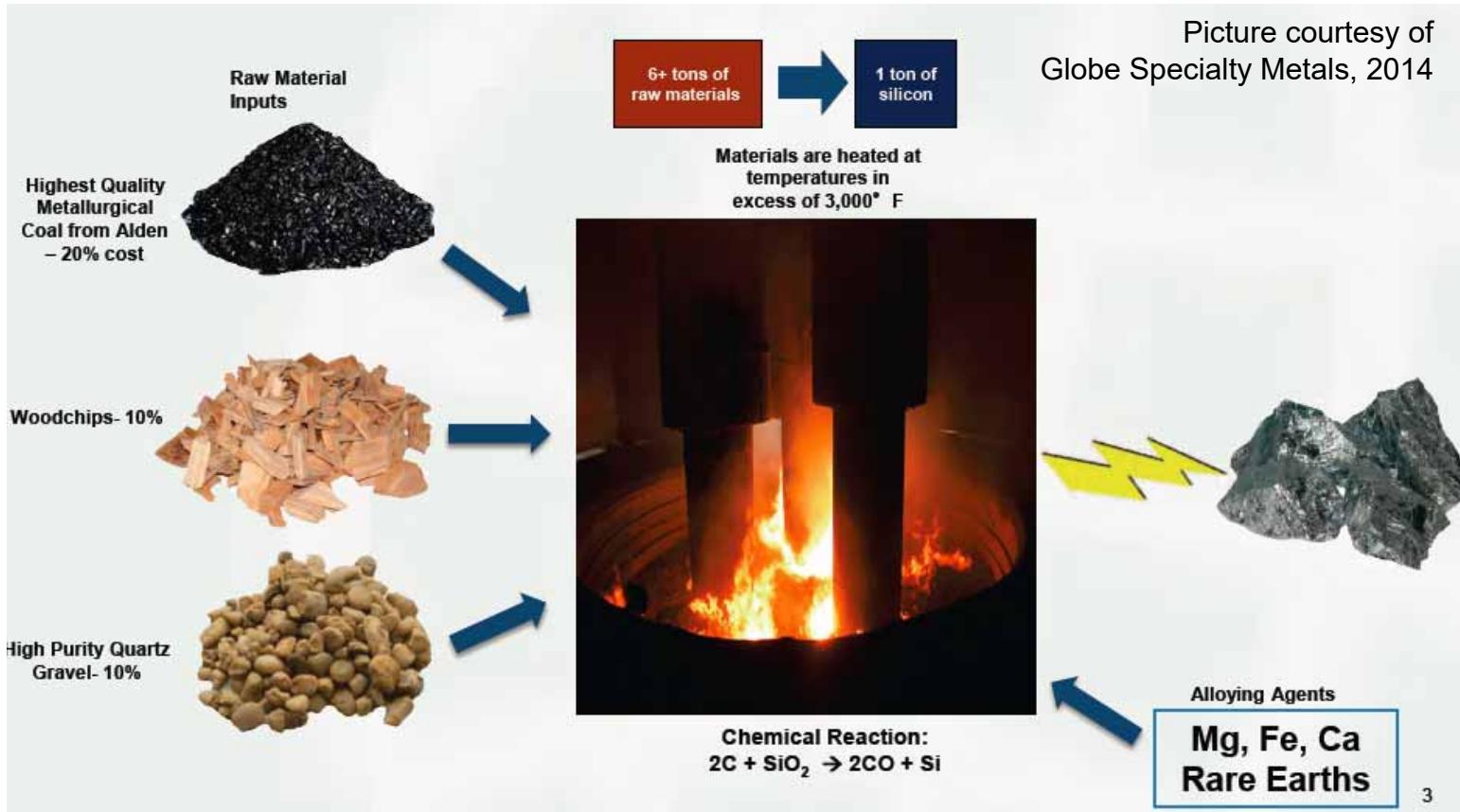


6 tons of Raw Material = 1 ton of SiMe

## PRODUCTION COST BREAKDOWN

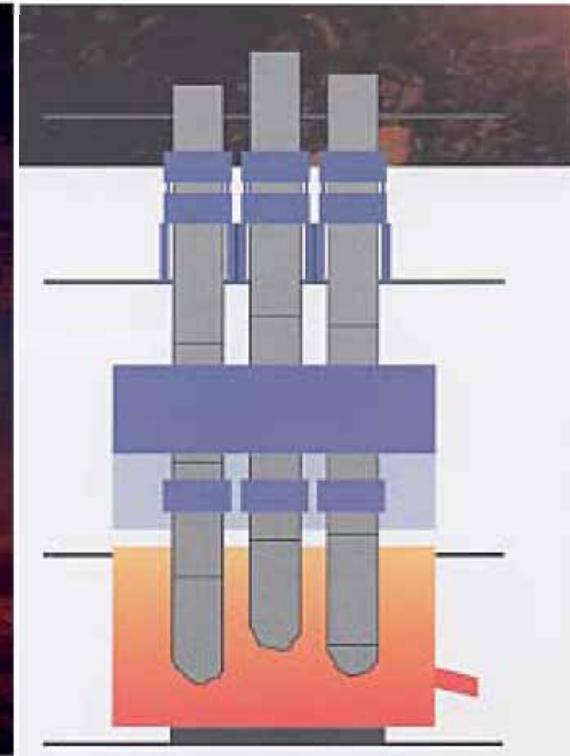
Source: Ferroglobe, CRU

# How is Metallurgical Si Made?



Reduction of quartz in a submerged electric arc furnace. Highly energy intensive process. Large plants. A medium sized EAF has a crucible diameter of 7 m, graphite electrodes each 15 m tall, weighing 20 tons each.

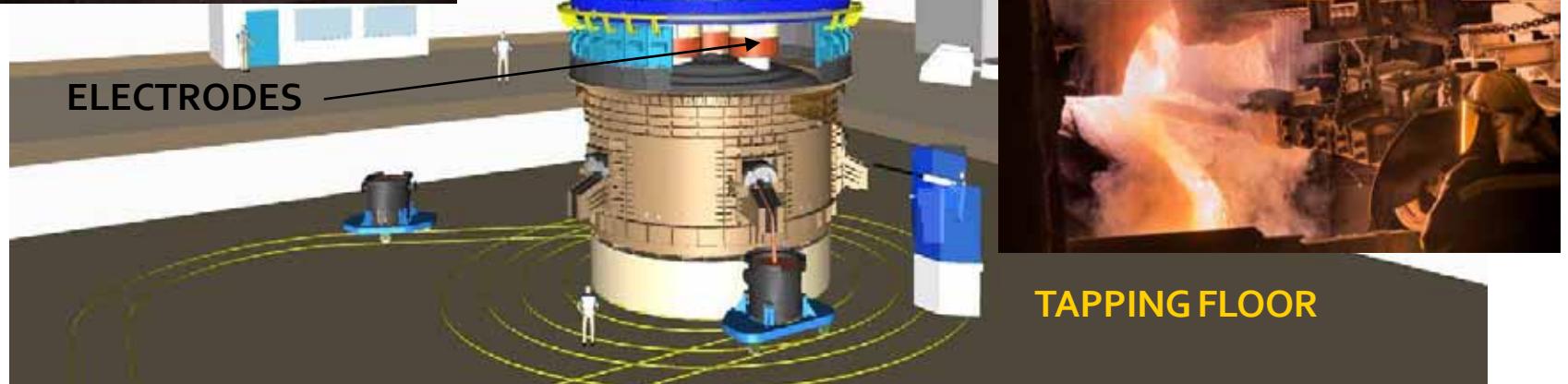
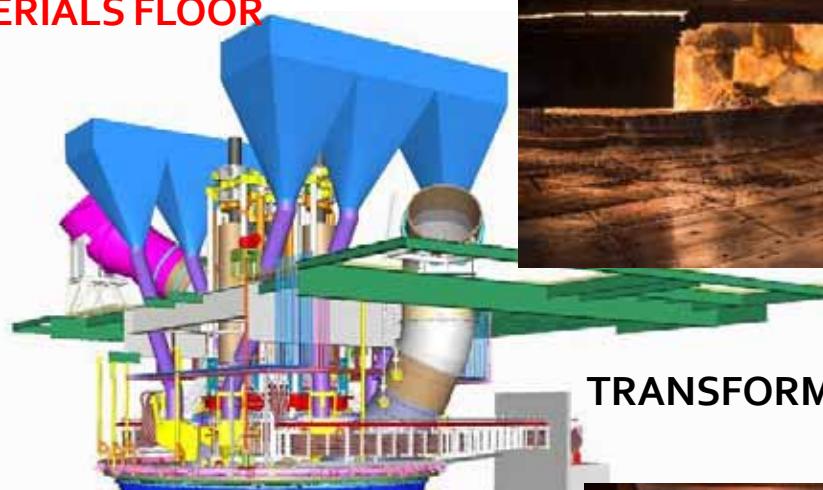
# How is Metallurgical Grade Silicon Made



A medium sized submerged arc furnace has a crucible diameter of about 7 metres. It is fed by three carbon electrode columns about 15 metres high and weighing about 20 tons each.

Source: [http://www.carbonandgraphite.org/pdf/silicon\\_production.pdf](http://www.carbonandgraphite.org/pdf/silicon_production.pdf)

# Si Smelting in a Submerged EAF



Graphics: Ferroglobe, 2017

# Facility layout – Ferroglobe, Polokwane, South Africa



Graphics: Ferroglobe, 2017

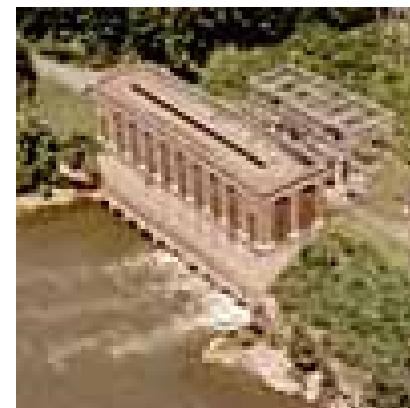
# For Si Metal Plants – Low Cost Electricity is Critical



GSM Alloy Plant



Electric Arc Furnace  
in Operation



Hawk's Nest  
Hydroelectric Plant

Source: Globe Specialty Metals

# North American Si Metal Plants



Mississippi Silicon  
Burnsville, MS  
36,000 ton



Ferroglobe  
Selma, AL  
31,000 ton



Quebec Silicon  
Becancour, QC  
50,000 ton



Ferroglobe  
Niagara Falls, NY  
30,000 ton



Ferroglobe  
Beverly, OH  
16,000 ton



Ferroglobe \*  
Alloy, WV  
75,000 ton



Dow Corning  
Mt. Meigs, AL  
42,000 ton

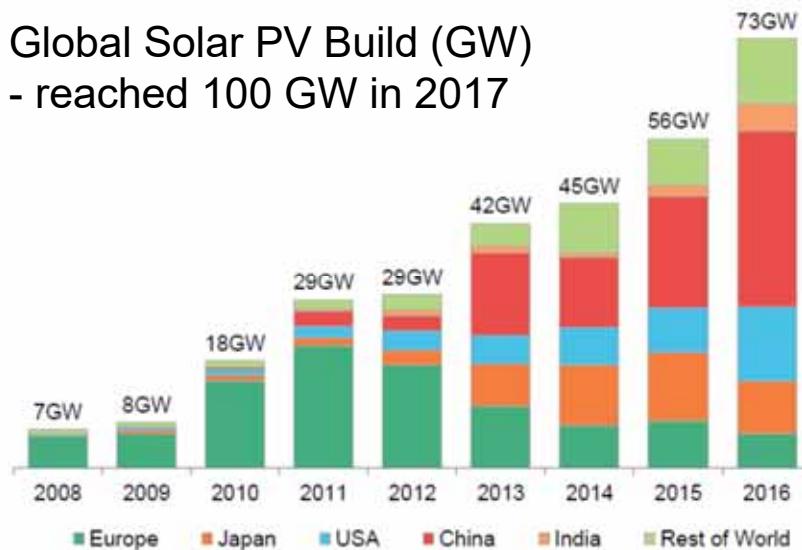


Images: Ferroglobe, DowCorning

# GROWING MG Si METAL MARKET

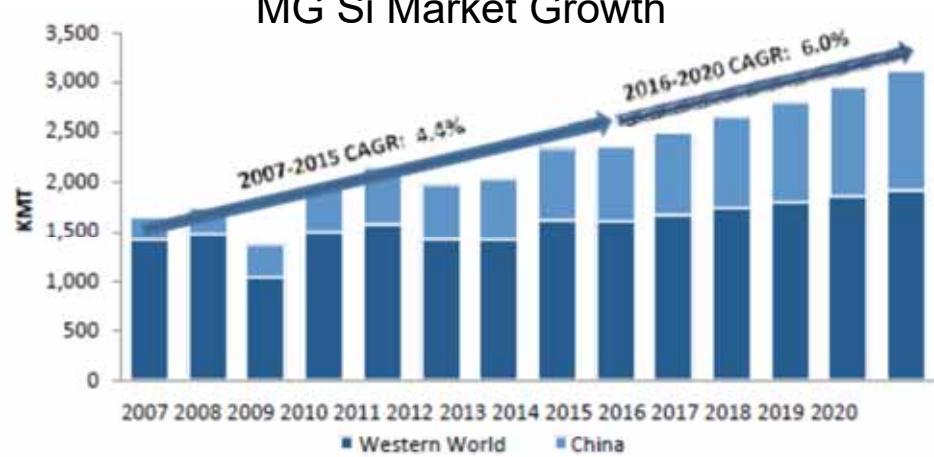
- MG Si consumption was 2.2 Million Tons
- Demand growing at 6.0% from 2016 – 2020
- Growth largely driven by the growing demand for polysilicon for PV panels

Global Solar PV Build (GW)  
- reached 100 GW in 2017



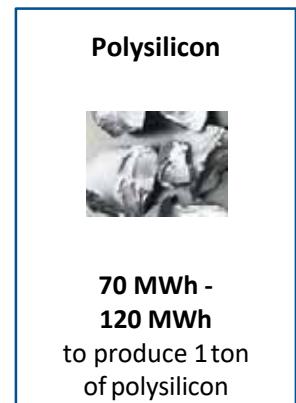
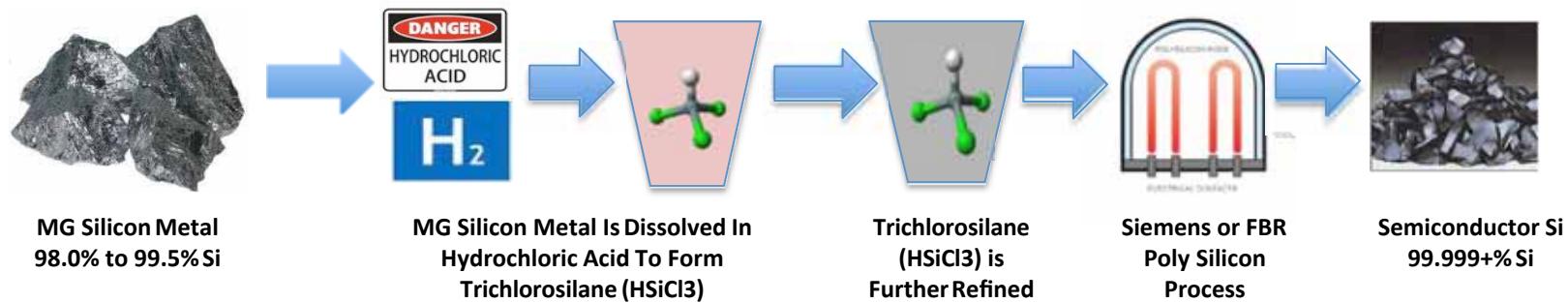
Source: Bloomberg New Energy Finance (2017)

MG Si Market Growth



Source: CRU 2015, Ferroglobe

# Si metal to Semiconductor grade Polysilicon



# Impurities in Silicon

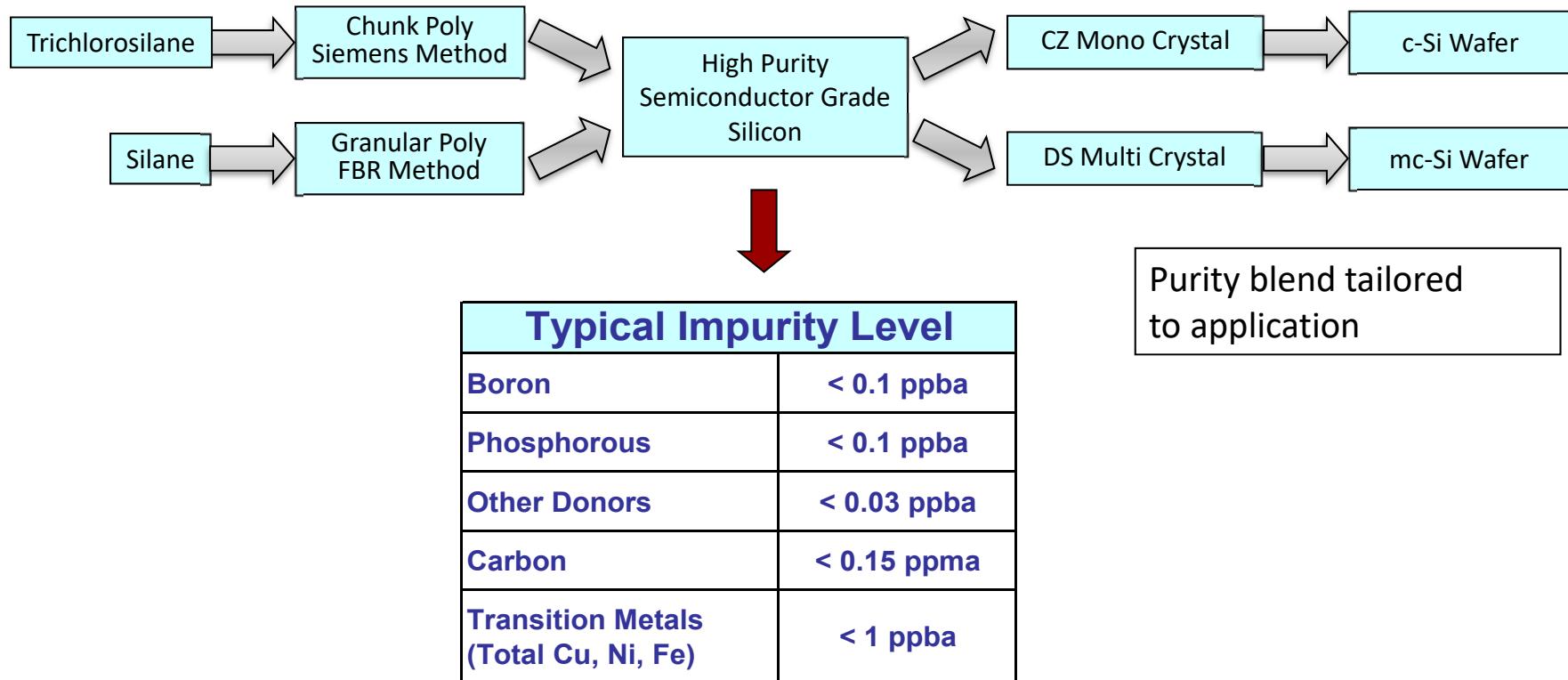


Metallurgical grade	Chemical grade	PolySilicon grade	Solar grade	High Purity
%Fe<0.5	%Fe<0.4	%Fe<0.3	%Fe<0.001	%Fe<0.001
%Ca<0.03	%Ca<0.03	%Ca<0.03	%Ca<0.0001	%Ca<0.0001
%Al<0.1	Min<%Al<Max	Min<%Al<Max	%Al<0.0001	%Al<0.0001
ppmP<limit	ppmP<limit	ppmP<limit	ppmP<1	ppmP : tailormade
	Trace elements <limit	ppmB<limit	ppmB<1	ppmB : tailormade
		Trace elements <limit	ppm others <10	ppm others : tailormade

## Semiconductor Grade Si

Typical Impurity Level	
Boron	< 0.1 ppba
Phosphorous	< 0.1 ppba
Other Donors	< 0.03 ppba
Carbon	< 0.15 ppma
Transition Metals (Total Cu, Ni, Fe)	< 1 ppba

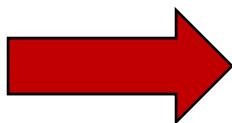
# Silanes to Polysilicon to Wafers



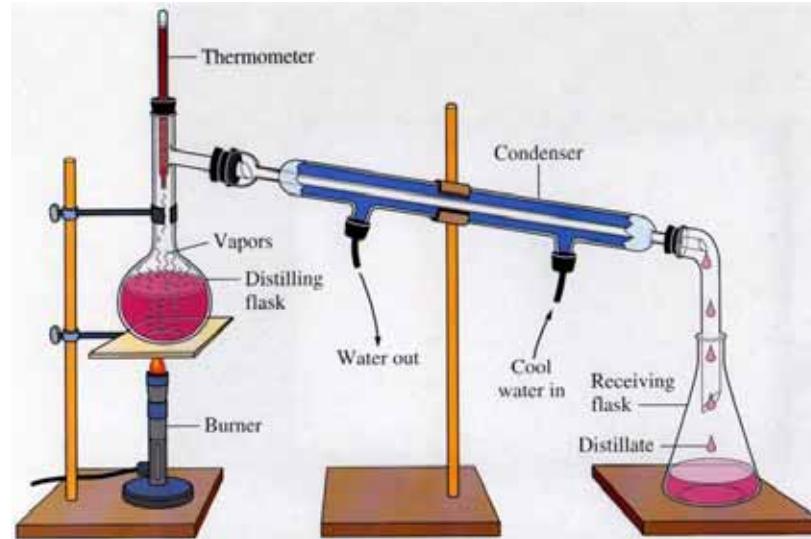
# Purification of Metallurgical Grade Silicon



Laboratory scale  
distillation



Impure TCS in



Pure TCS out



Industrial scale  
distillation

Graphics: Courtesy of Graham Fisher  
MEMC Electronic Materials

# Purification of Metallurgical Grade Silicon



Metallurgical silicon costs about \$2 per kg

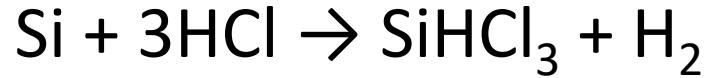
MG Si contains too many impurities for use in semiconductors or solar cells

In order to purify it we do this:

- 1) Convert it to a liquid compound containing silicon
- 2) Distillation of the liquid to purify it
- 3) Extract silicon from the high purity liquid

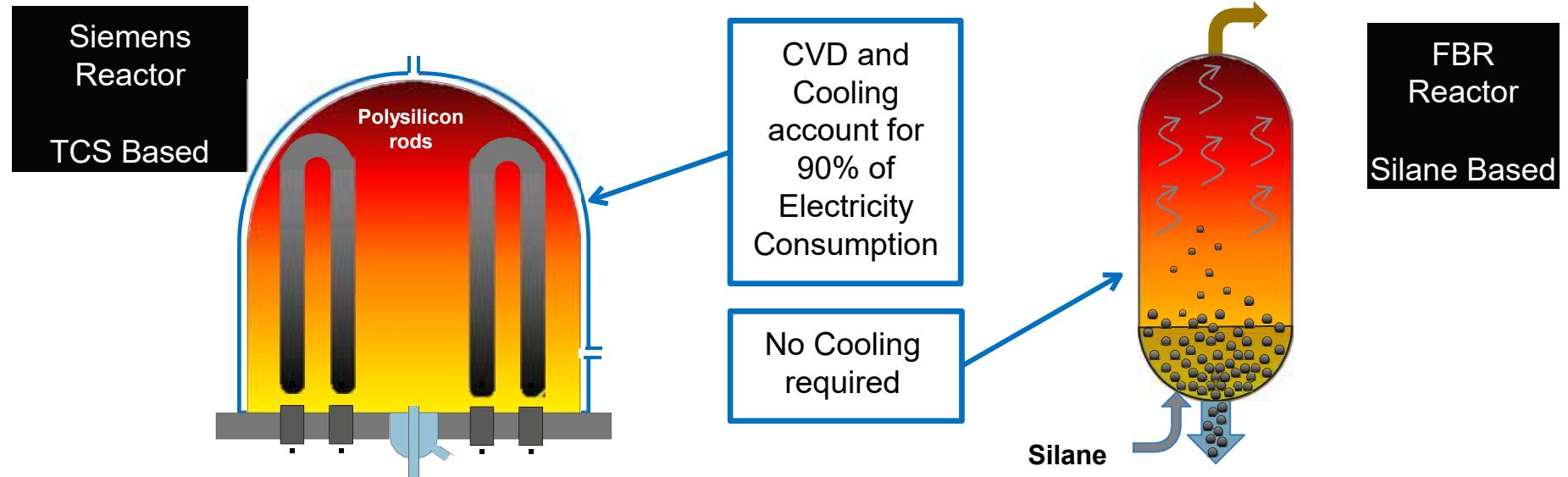
Step 1 is achieved through the following reaction

Silicon + Hydrochloric acid → Trichlorosilane + Hydrogen  
Solid                    Liquid                    Liquid                    Gas



TriChloroSilane is often referred to as TCS

# Polysilicon Production



## Siemens Process

- Mature 40 year technology
- Batch process
- Requires post processing
- High cash cost

## FBR Process

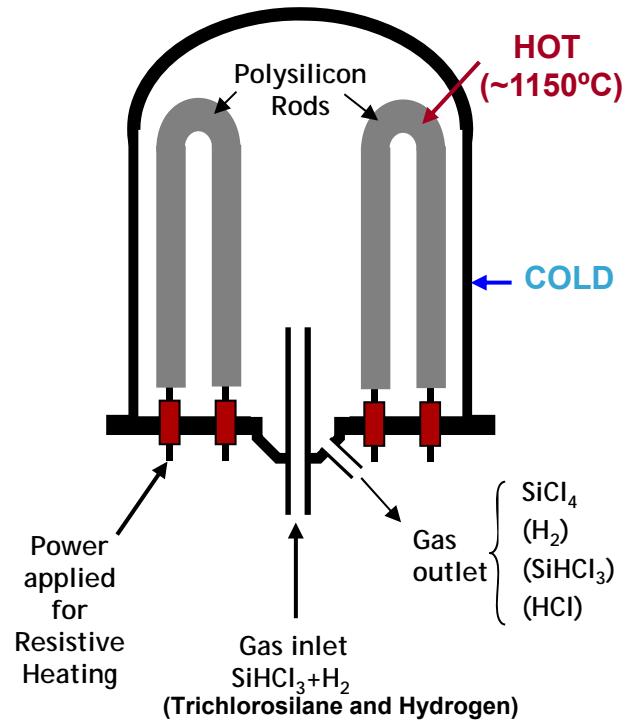
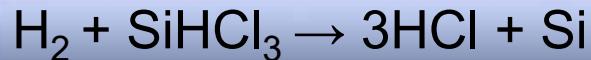
- Energy efficient
- Continuous production
- Lower cash cost

# Siemens Process

- Convert metallurgical Silicon into Trichlorosilanes (TCS)



- Purify TCS in distillation columns
- Recover pure Si using Chemical Vapor Deposition (CVD)



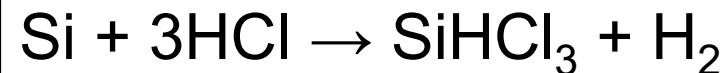
Cold wall reactor, high energy consumption. TCS conversion per pass is around 15%, recycling and lower productivity

# Siemens Process

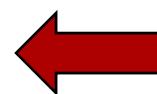
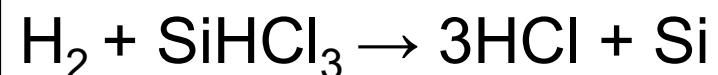


The Siemens process is commonly used to produce semiconductor grade silicon

We used this reaction to make TCS:

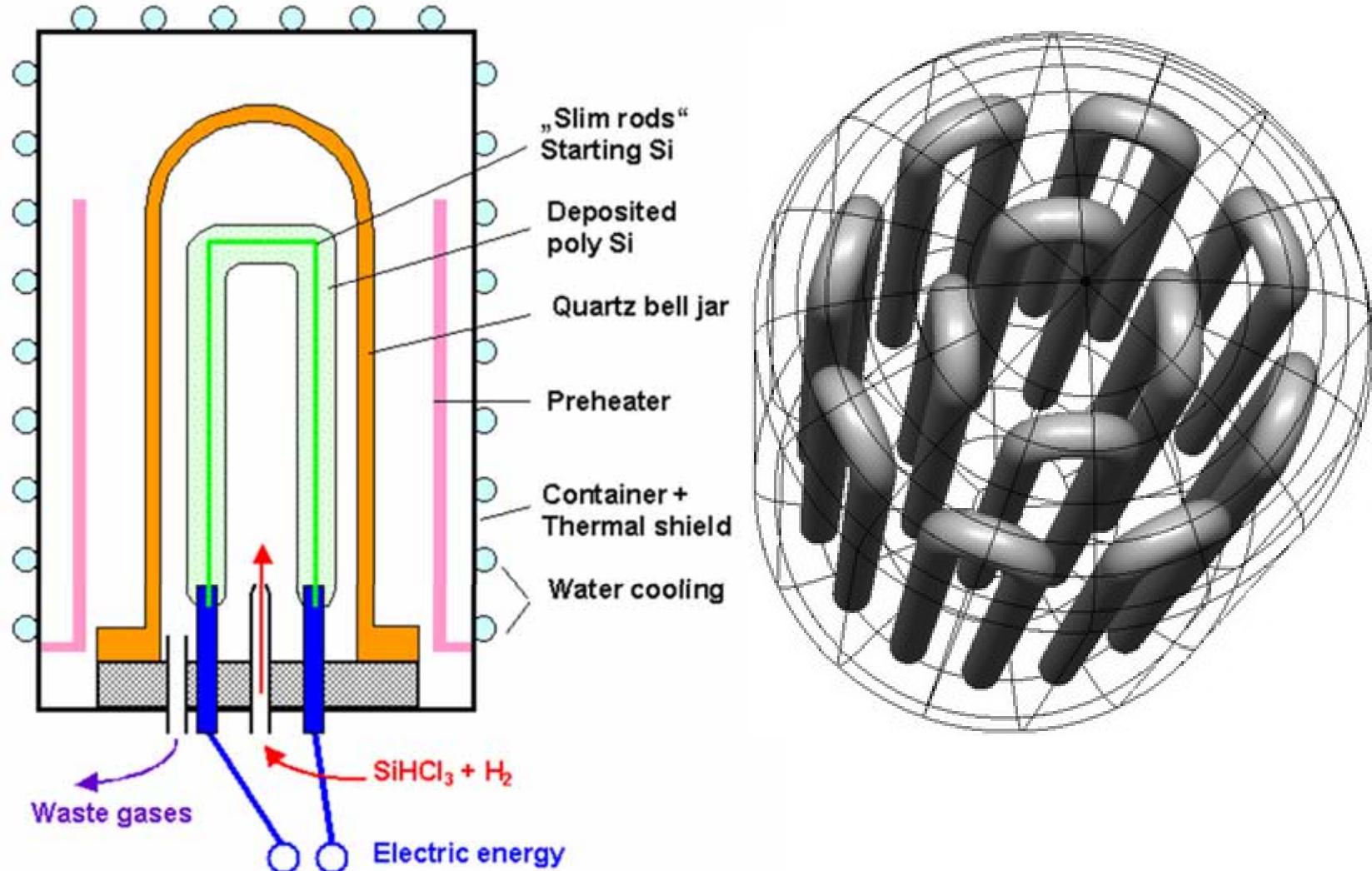


To go back to silicon we just run the same reaction backwards!



The reaction is run in a Siemens reactor that looks like this.

# Inside the Siemens Reactor



# Siemens Polysilicon



Siemen's reactor



Before polysilicon  
growth – slim rods



As grown polysilicon  
rods after a reactor run

Source: GR Fisher, Proc. IEEE, vol. 100, pp. 1454 – 1474, April 2012

**80% of the worlds polysilicon is produced using the  
Siemen's process developed in the 1950's.**

# Insides of Siemens Reactor



Before



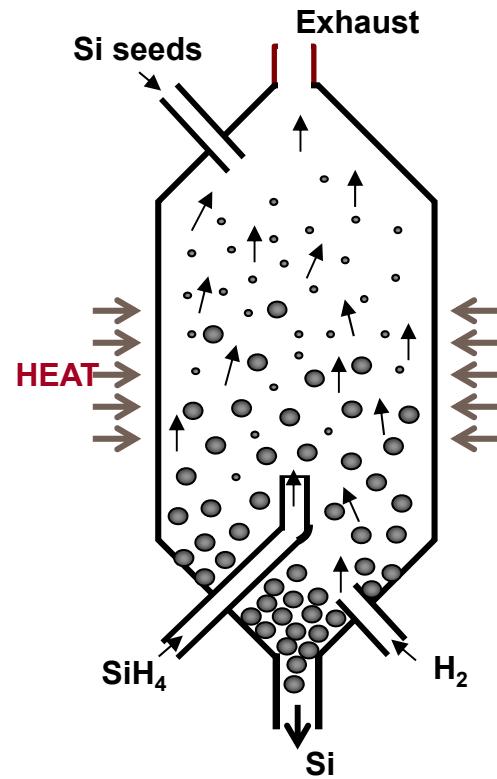
After

# Si from Siemens Process – Chunk poly



Graphics: Graham Fisher  
MEMC Electronic Materials

# Fluidized Bed Reactor Production



Hot wall reactors  
Higher throughput



**Granular polysilicon has a higher packing density in the crucible and, because it flows, can be used to recharge hot crucibles lowering cost and improves throughput of crystal growth processes.**

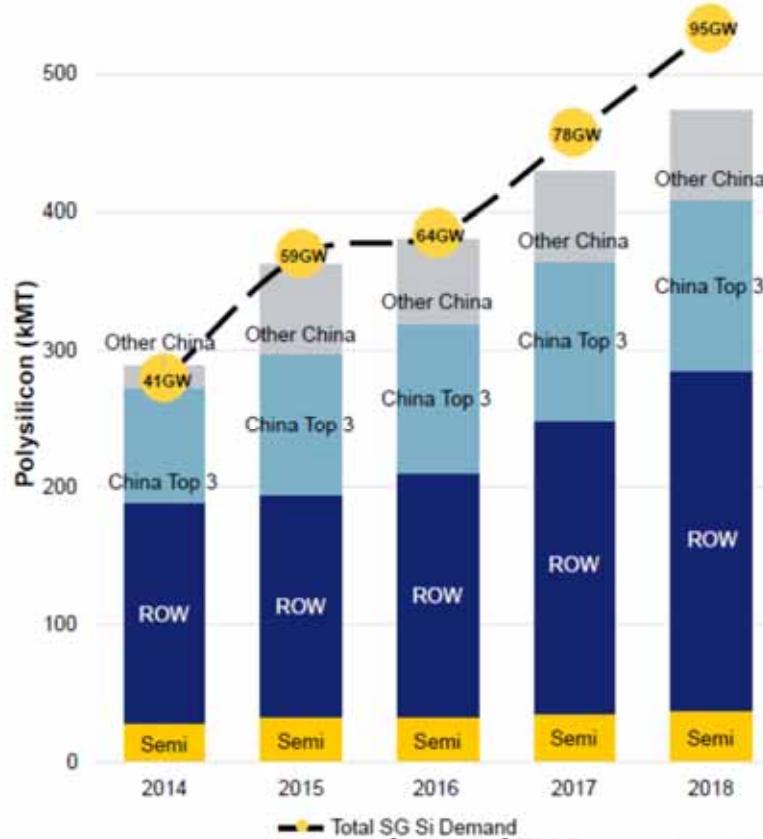
# Poly-Si Production – Large Chemical Plants



Large capital outlays  
10000 ton capacity plant ~\$500M



# Growth in Polysilicon Production



Source: GTM Research, 2016



Source: Polysilicon & wafer rankings  
PV Magazine, March 2017

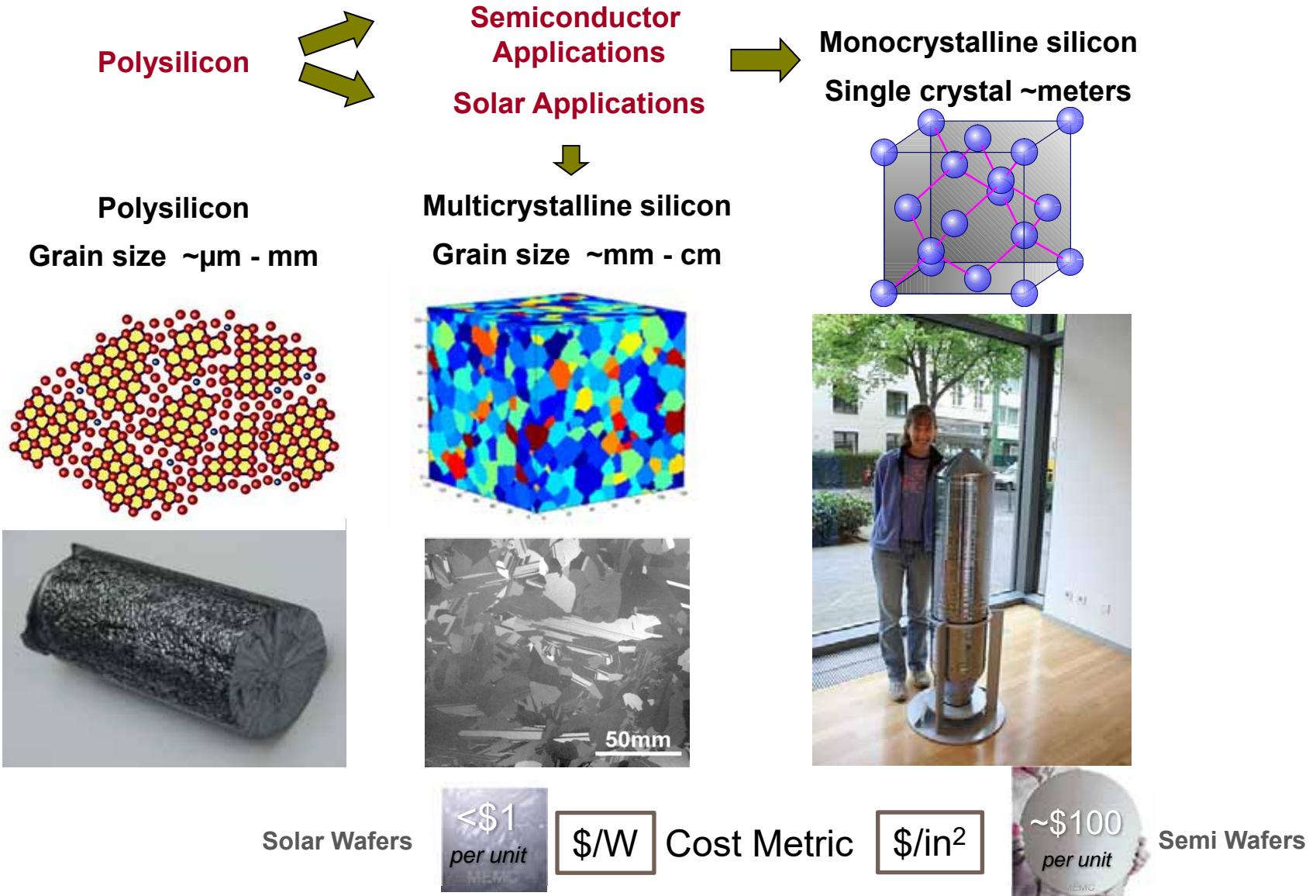
Over 90% of polysilicon is consumed by the PV Industry  
Size of the PV market in 2017: 75 GW; 2017: 100 GW, Si used <5g/W

# Crystal Growth and Wafer Manufacturing

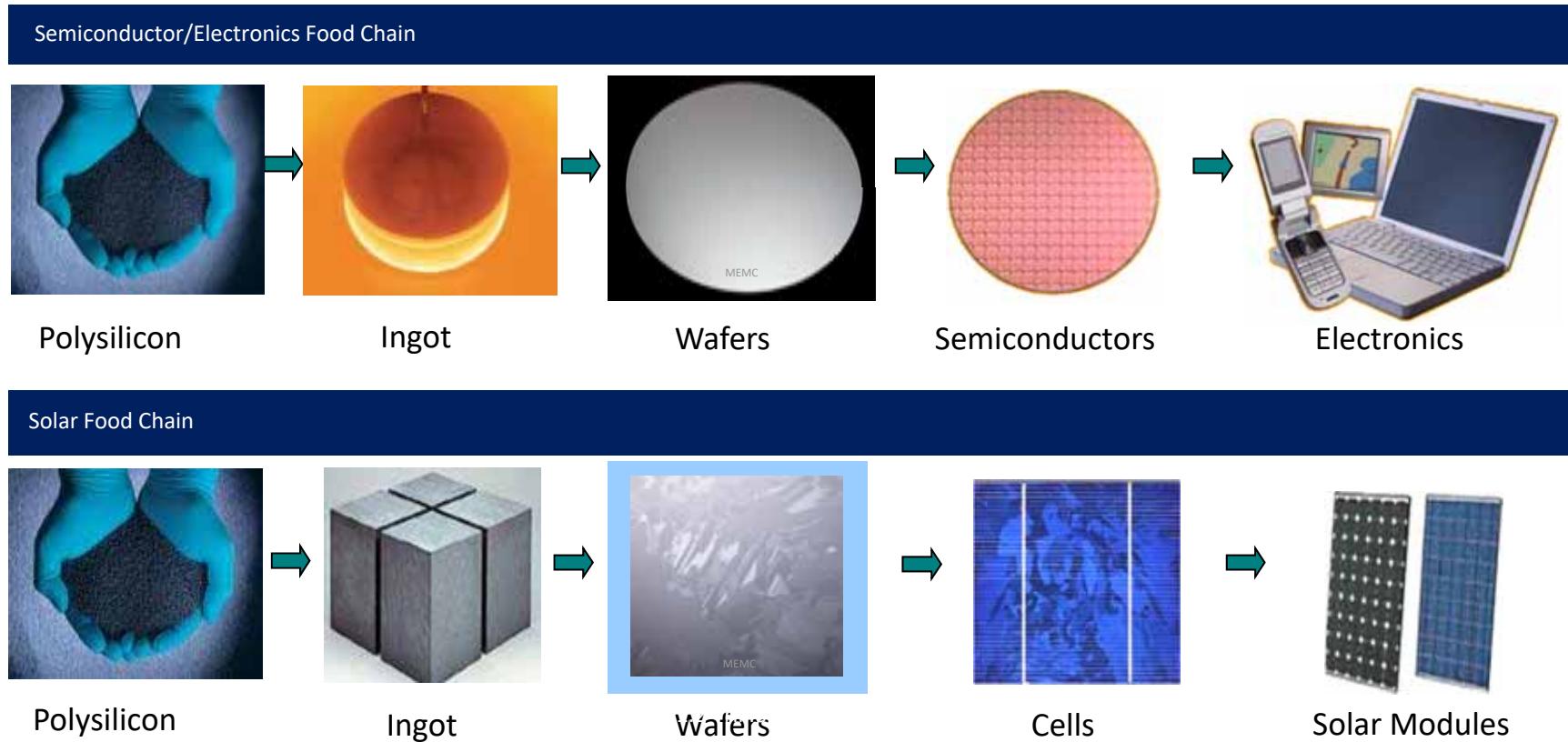


- Czochralski(CZ) growth remains the dominant process for monocrystalline crystal growth
- Significant advances in Continuous CZ process
- Directional solidification (DS) for multicrystalline wafers

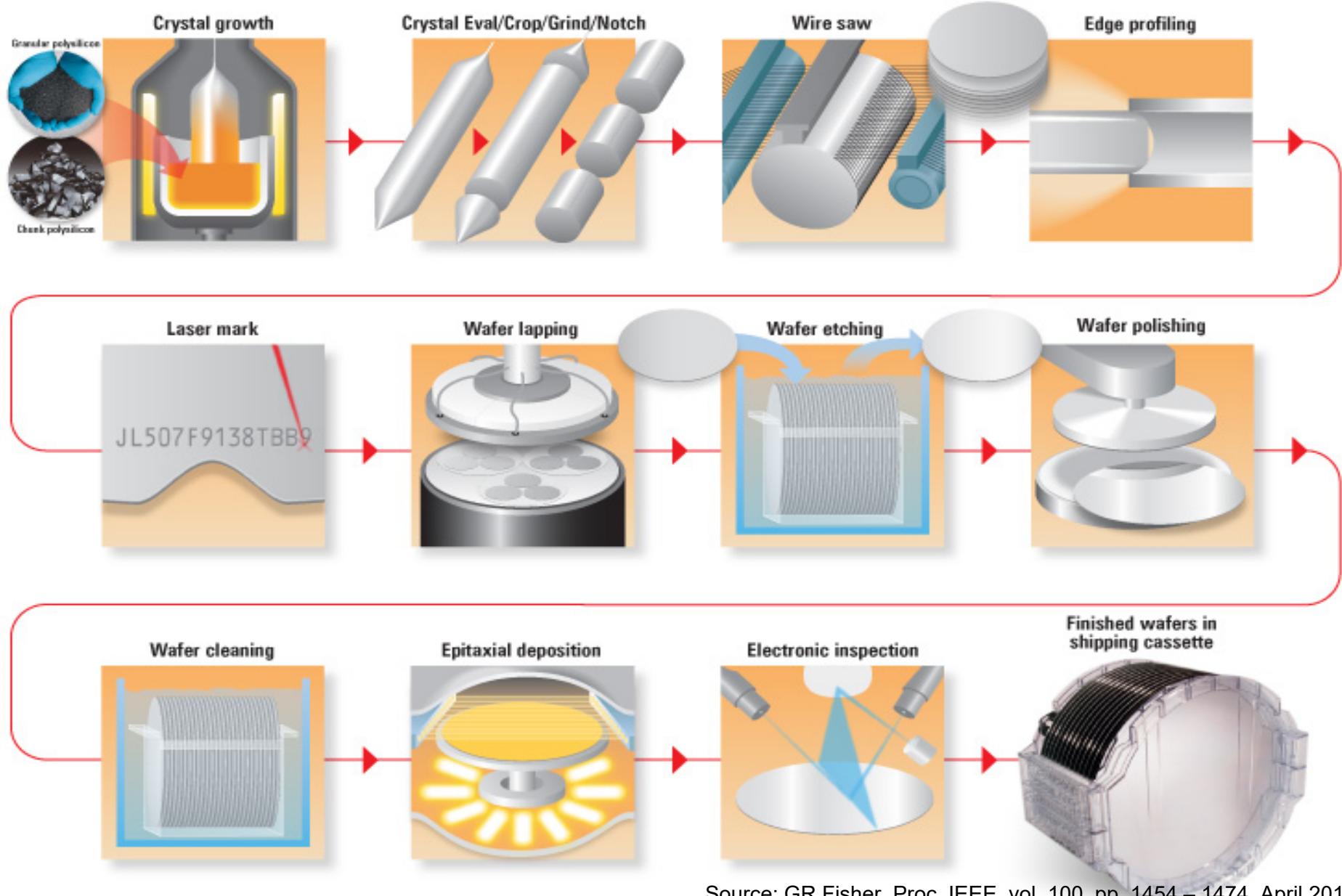
# Solar vs. Semiconductor Silicon



# Semiconductor vs. Solar

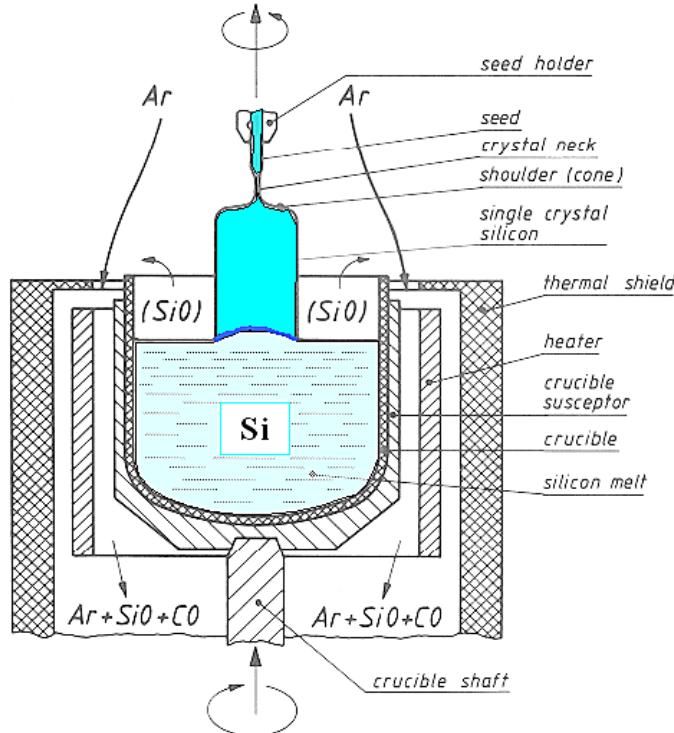


# Monocrystalline Si Wafer Manufacturing Process

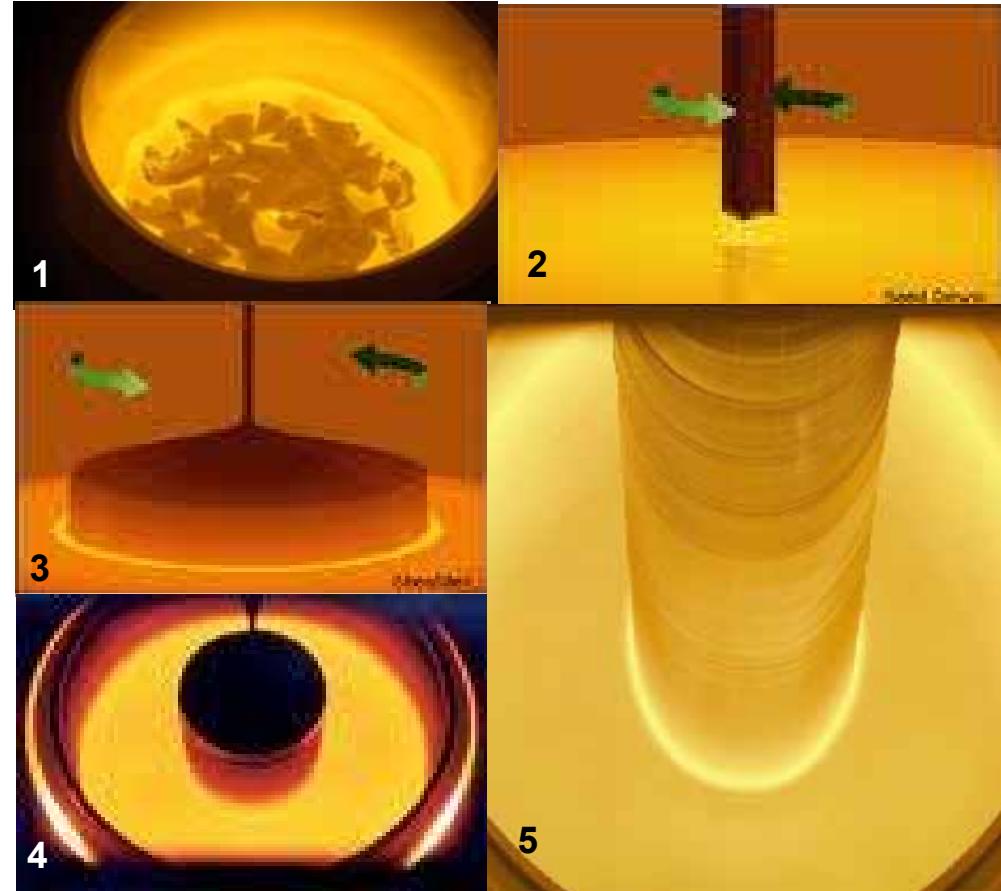


Source: GR Fisher, Proc. IEEE, vol. 100, pp. 1454 – 1474, April 2012  
MEMC 50<sup>th</sup> Anniversary Volume, 2009

# Crystalline Si Czochralski Crystal Growth



**Crystal Puller**



Various stages of Czochralski crystal growth,  
1 Meltdown, 2 Seed Dip, 3 Top, 4 Shoulder, 5 Body

Source: GR Fisher, Proc. IEEE, vol. 100, pp. 1454 – 1474, April 2012

# Czochralski Method for Silicon Crystal Growth

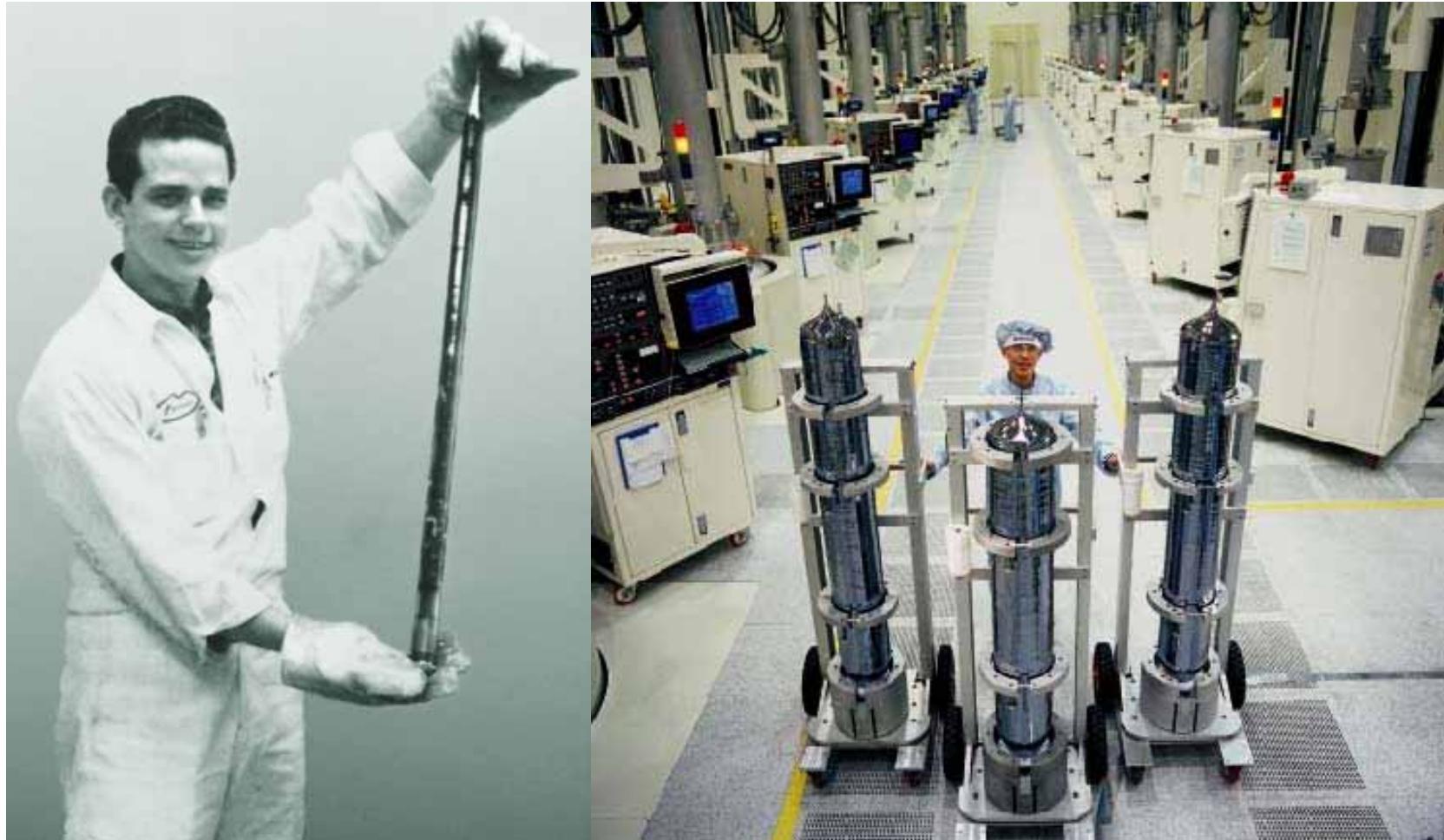


Crystal Puller



Product

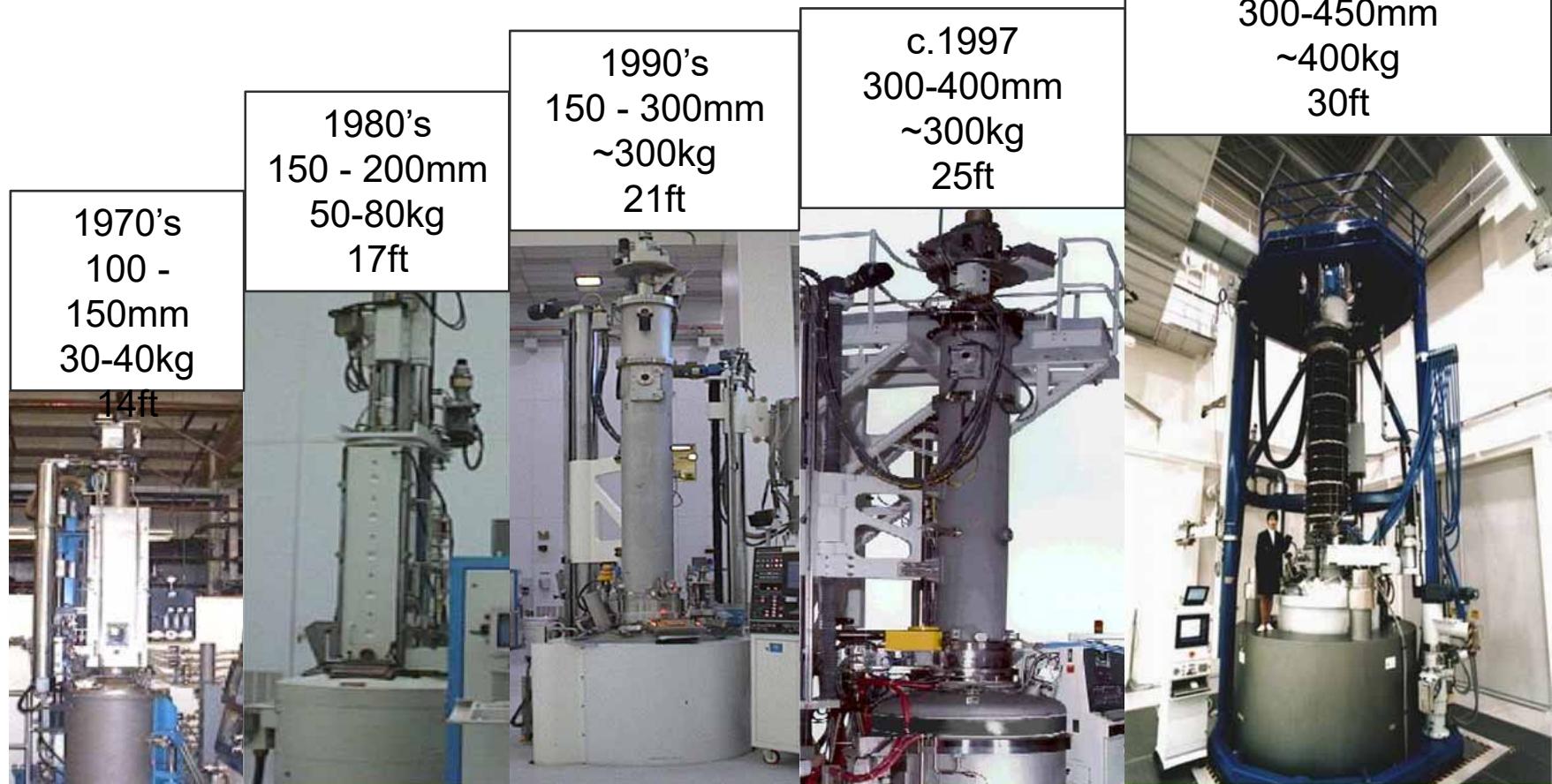
# Typical Factory Floor



Early days of Czochralski(CZ) growth crystals were small and easy to handle. Current generation crystal are large, heavy and need specialized handling equipment.

Source: MEMC 50<sup>th</sup> Anniversary Volume, 2009

# Crystal Puller Evolution



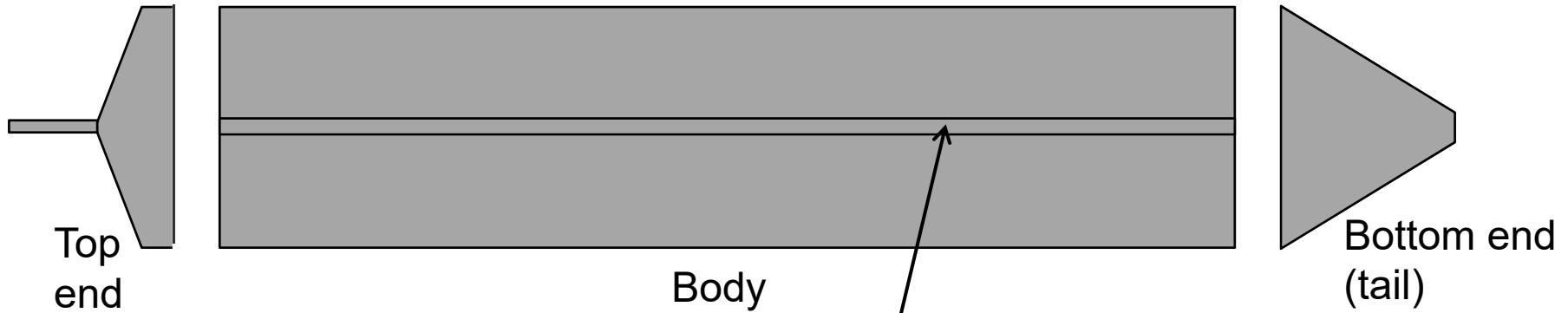
Examples of progress in Czochralski crystal pullers from 1970 through current diameter capability. Showing approximate period, crystal diameters, typical polysilicon charge weight and approximate height of the equipment above the working floor. Later models have services (water, argon, vacuum) below floor level. (Right hand photo shown is courtesy of Super Silicon Institute (SSI).)

Source: GR Fisher, Proc. IEEE, vol. 100, pp. 1454 – 1474, April 2012

# Continuous Czochralski Crystal Growth



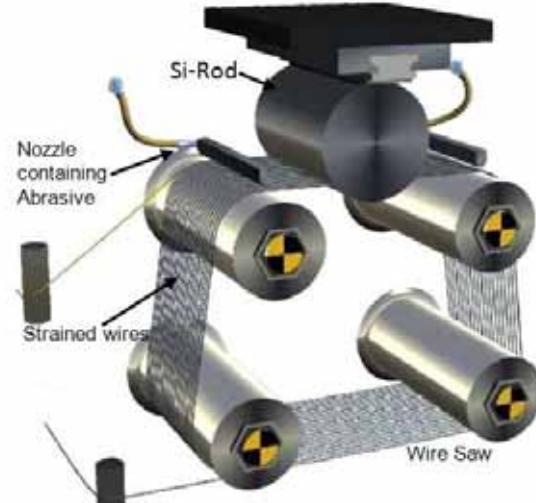
# Wafer Slicing



Before getting the ingot ready for slicing, top and tail ends are removed. Orientation of the crystal lattice determined by x-ray diffraction.

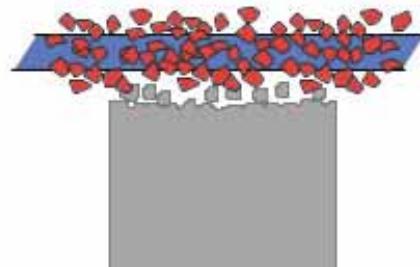
A notch is cut on outside aligned with the crystal lattice. Later when the wafers are cut from the ingot, each one has a notch which indicates the orientation of the crystal lattice.

# Wafer Slicing

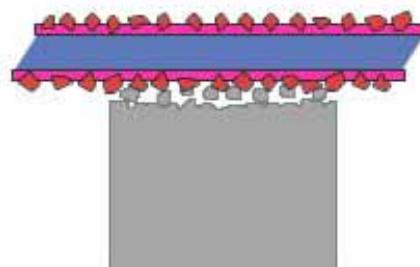


Solar wafers 180 - 220  $\mu\text{m}$  thick, typical Semiconductor wafer  $\sim 900\mu\text{m}$

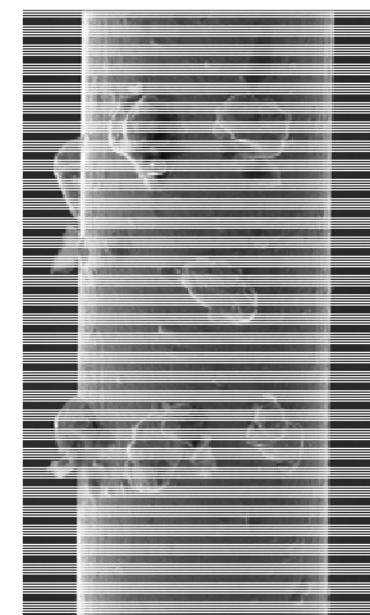
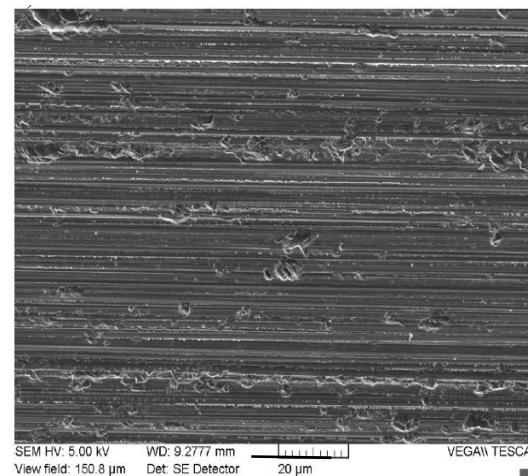
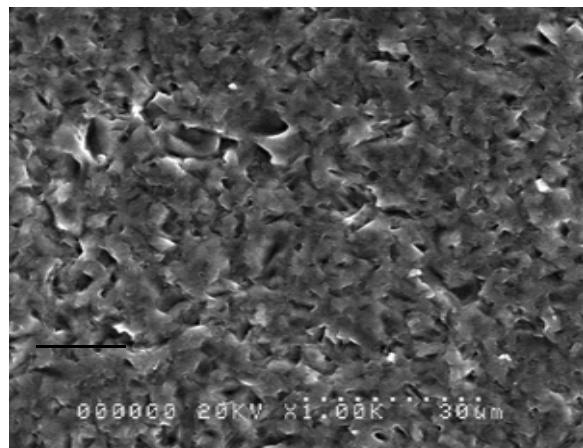
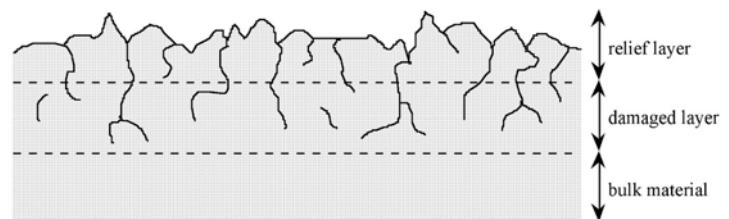
# Wafer Slicing



Slurry-based method



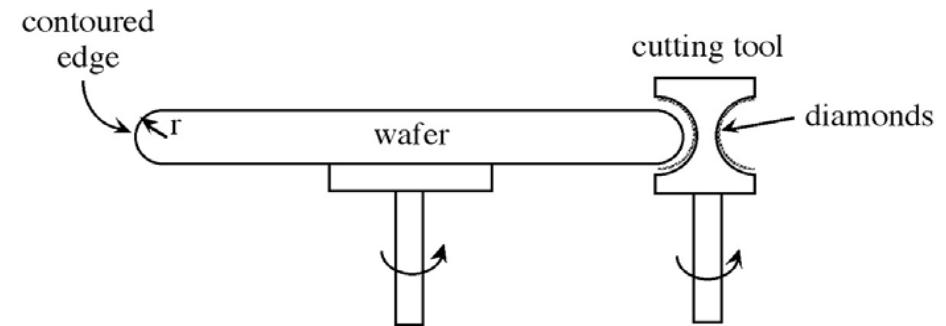
Fixed Abrasives method



# Edge Profiling

## Purpose

- Produce a rounded wafer edge that is tougher and more resistant to chipping during handling
- Minimize edge surface roughness
- Minimize depth of damage on edge



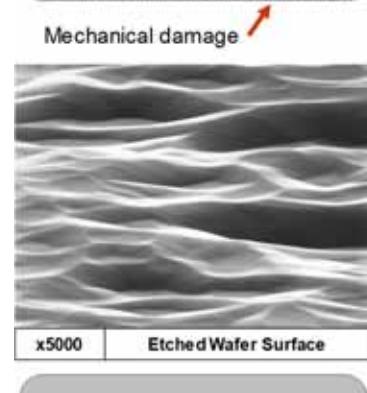
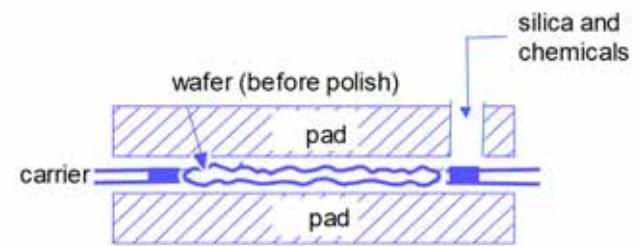
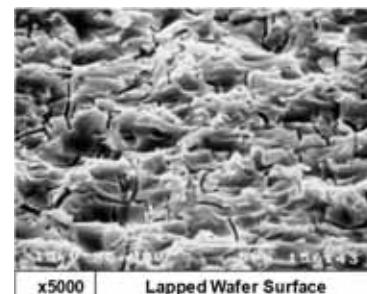
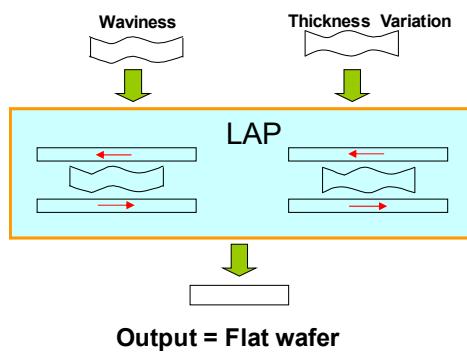
**Before**



**After**

# Lapping, Etching and Polishing

Lapping removes saw damage and produce a flat wafer. Etching and chemical mechanical polishing processes further improve the surface to almost atomically smooth.



Damage removed  
Flat but not smooth



# Finished Semiconductor Wafer

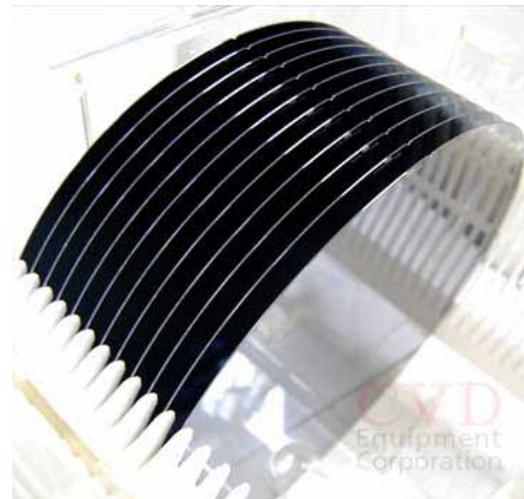


Flat to within 250nm

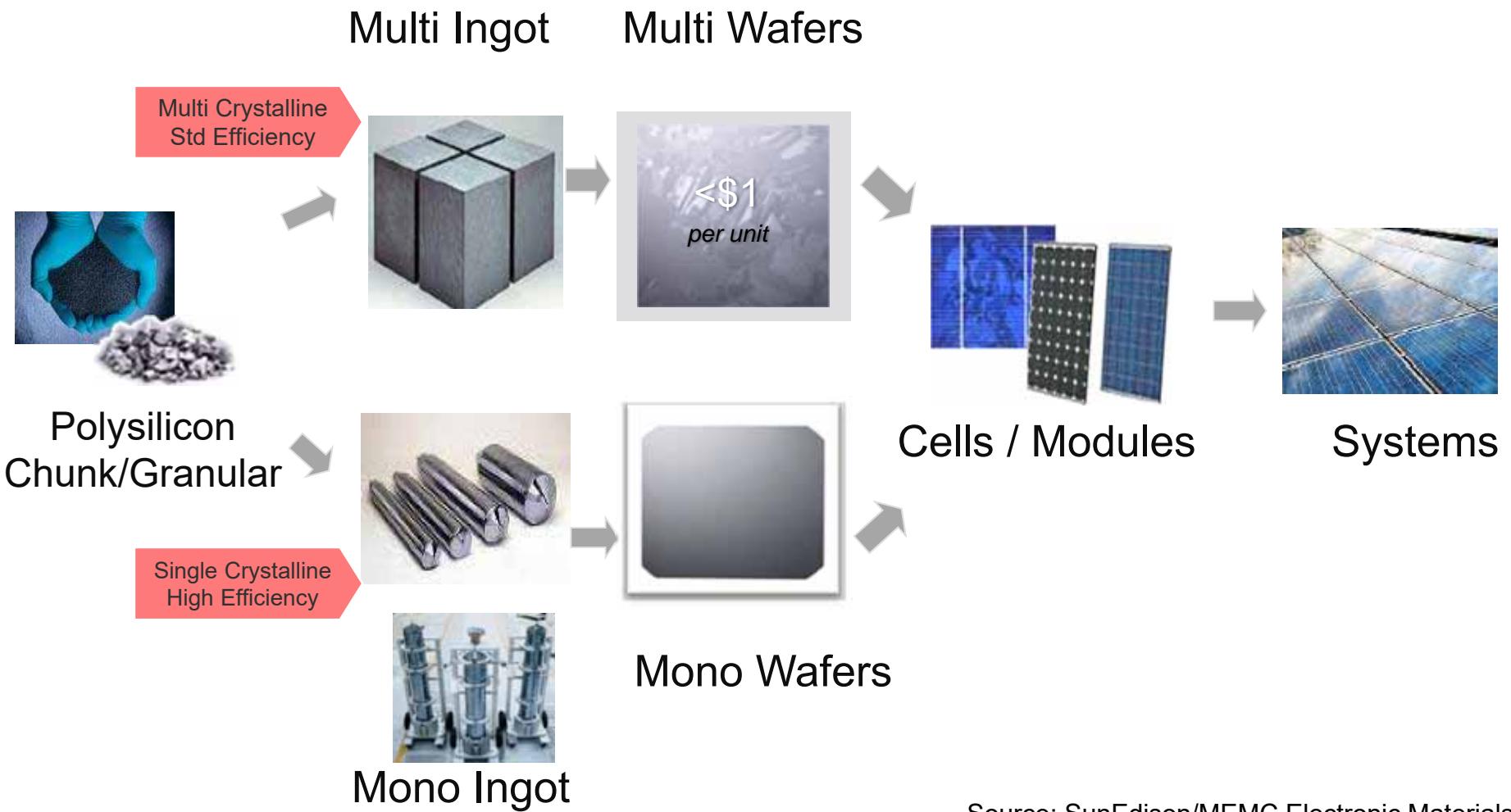
- equivalent to a football field flat to within 2 thousandth of an inch

Clean  $<10^{10}$  unwanted impurity atoms/cm<sup>2</sup>

Purity  $<10^{11}$  metal atoms/cm<sup>3</sup>



# Silicon PV Food Chain

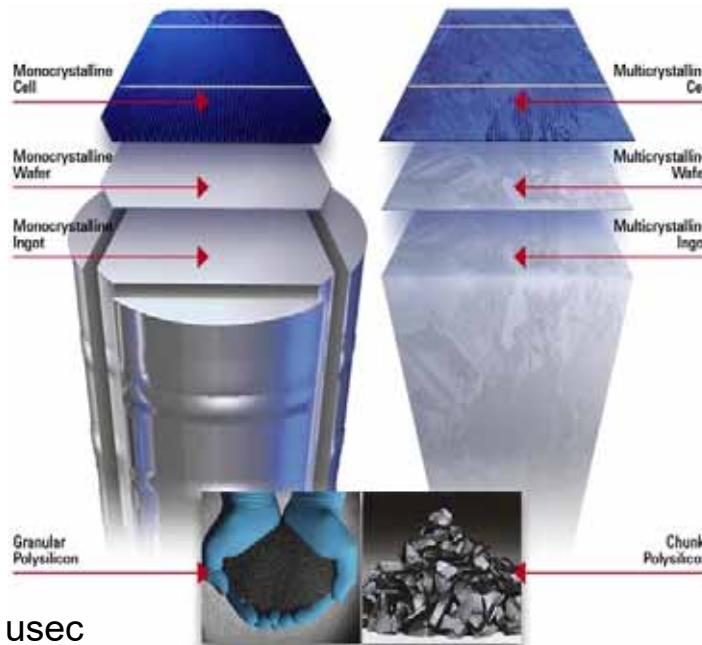


Source: SunEdison/MEMC Electronic Materials

# Mono vs. Multi Silicon Wafers

## Mono Characteristics

- P-type/N-type
- Resistivity ~ 0.5-3ohm-cm
- Nominal thickness ~ <=200um
- Oxygen < ~ 20ppma
- Carbon < ~ 1ppma
- Dislocation-free
- Lifetime > 10usec on block
- Passivated lifetime > 100-1000 usec
- Single orientation = lower reflectivity texturing

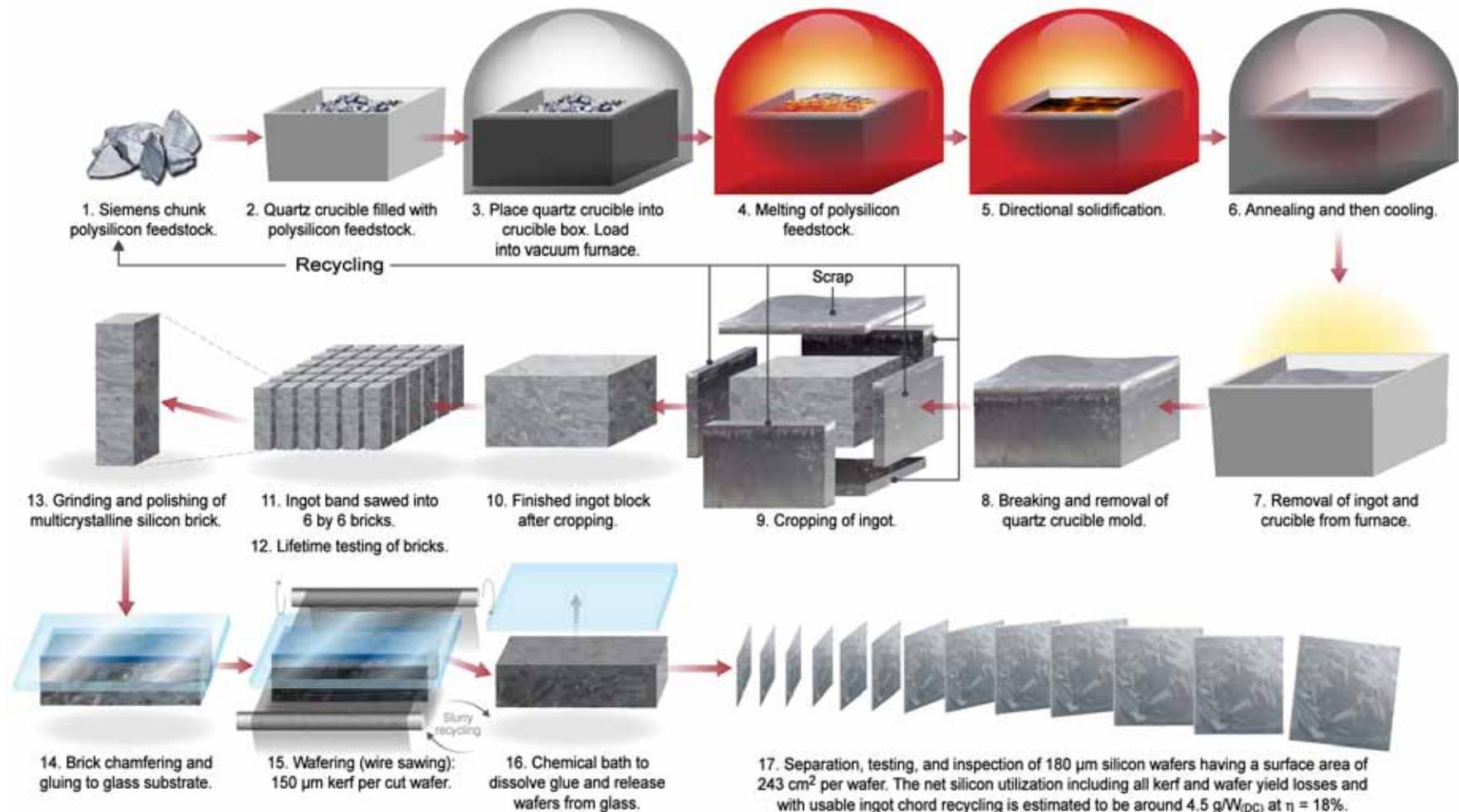


## Multi Characteristics

- P-type
- Resistivity ~ 0.5-3ohm-cm
- Nominal thickness ~ 200um
- Oxygen < ~ 10ppma
- Carbon < ~ 10ppma
- Dislocations ~ E5/cm3
- Lifetime > 2usec on block
- Passivated lifetime > 10usec
- Multi orientation = higher reflectivity texturing

***Choice depends on application and cost requirements***

# Multicrystalline Si Wafer Manufacturing Process

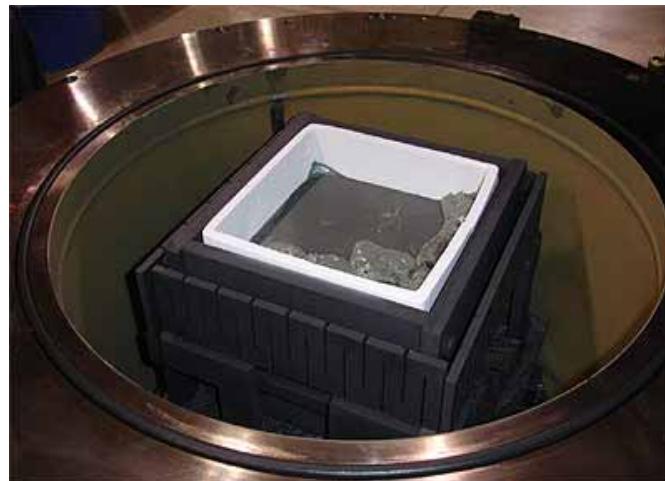


Graphic: courtesy of NREL, 2015

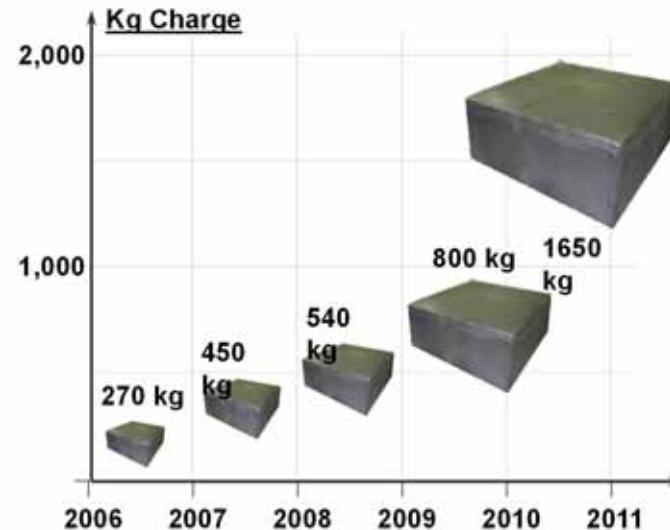
# mc-Si Directional Solidification



Casting furnace



Open furnace after casting



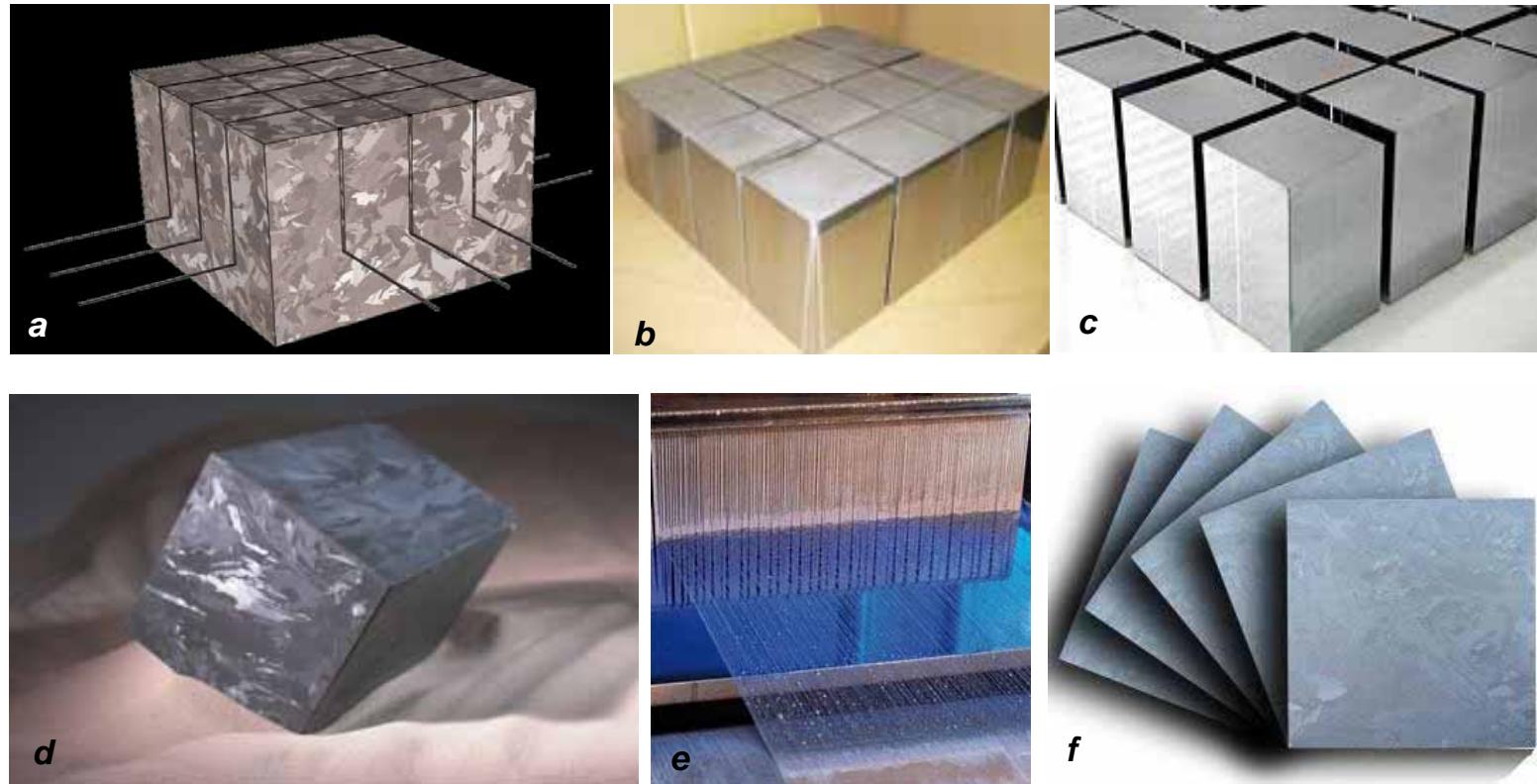
A . Deshpande, 2012 NREL Silicon Workshop  
Images Courtesy of MEMC



Finished casting

DSS allows for large cast

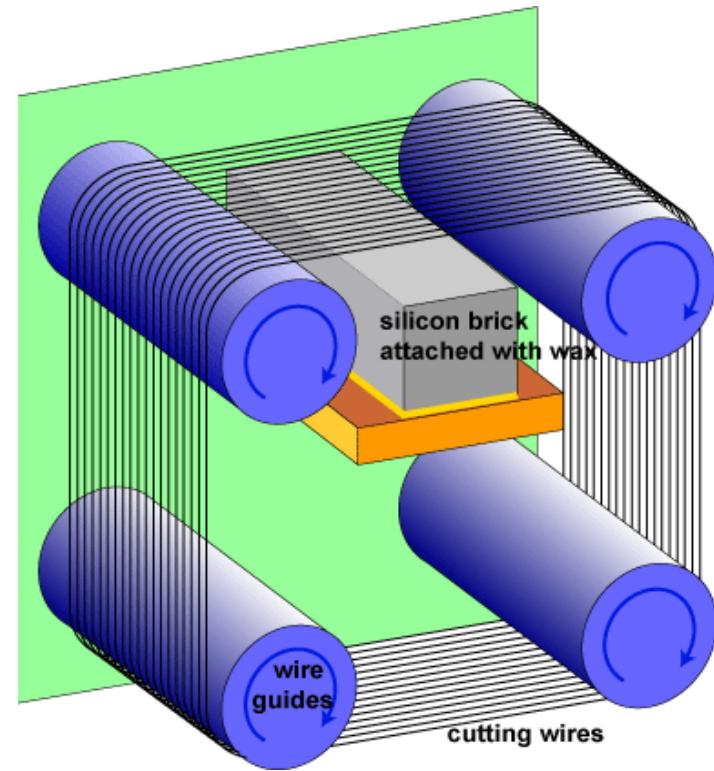
# Fabrication of Solar Wafers



*(a & b) Sawn into bricks ; (c) Bricks are ground; (d) chamfered, then (e)sawed into wafers, (f) polished wafers*

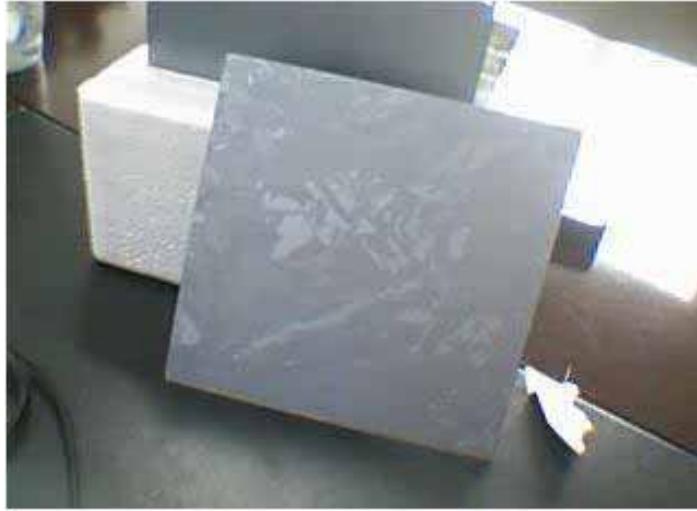
A . Deshpande, MEMC Electronic Materials

# Wafer Slicing



Solar wafers 180 - 220  $\mu\text{m}$  thick, typical Semiconductor wafer  $\sim 900\mu\text{m}$

# Finished Solar Wafer

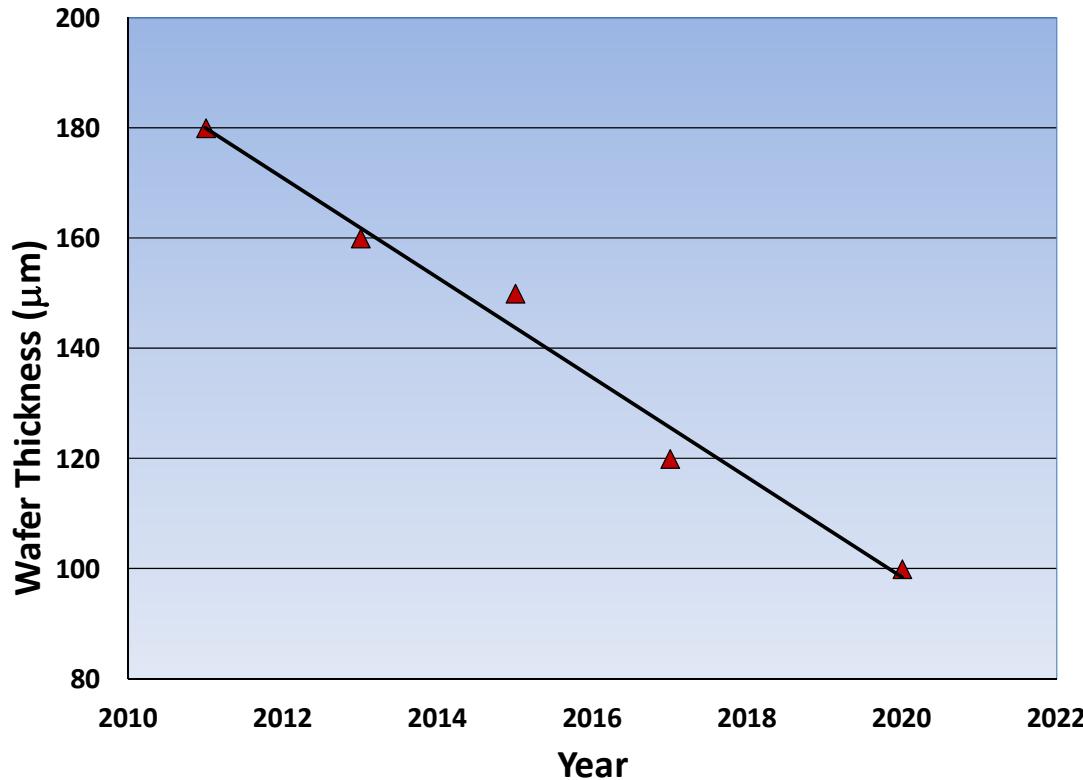


For solar applications cost is key

Processing downstream from slicing is limited to cleaning and an etch to remove some saw damage and add texture.

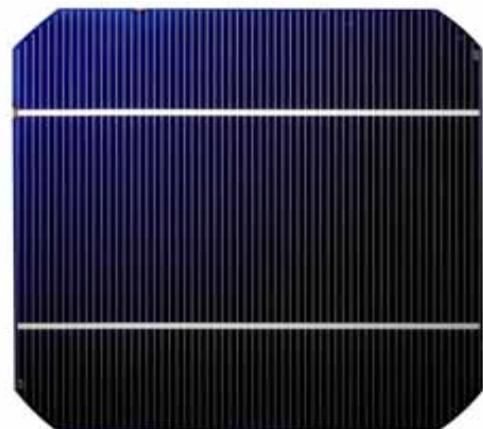


# Trends in Wafer Technology

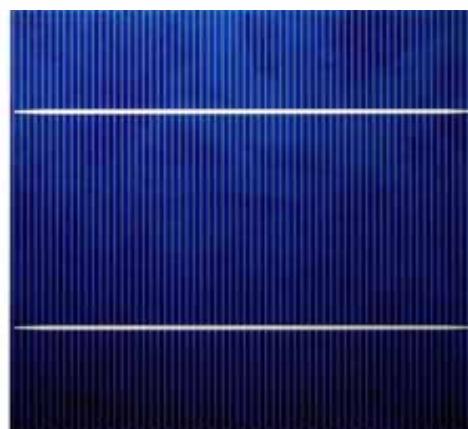


Projected trend in minimum wafer thickness processed in mass production of solar cells  
(International Technology Roadmap for Photovoltaics, SEMI PVGroup/ITRPV, 2011).

# Wafers to Cell and Modules



156 mm monocrystalline solar wafer and cell.

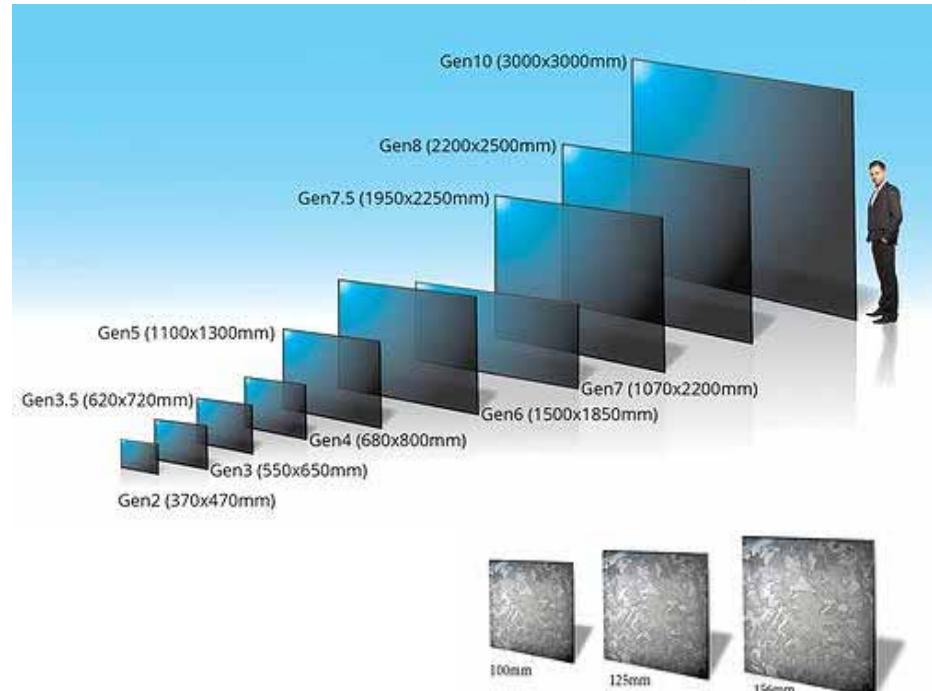
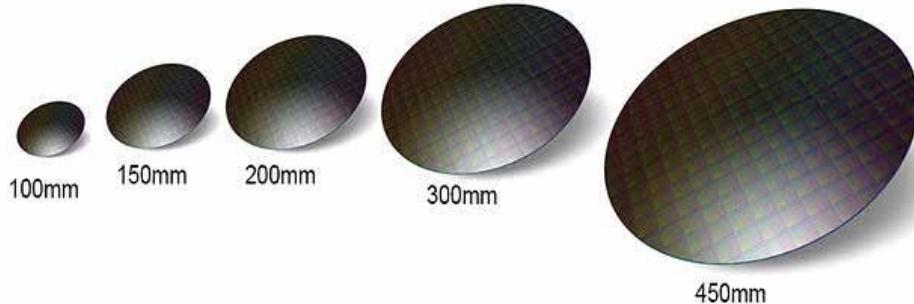


156mm multi-crystalline solar wafer and cell



Solar cell module  
(from multi-crystalline wafers)

# Scaling (size, volume, and performance)



## ***Microelectronics***

Si Substrates

20x scaling (30 yr)

50, 100, 150, 200, 300 mm

## ***Flat Panel Displays***

Glass Substrates

50x scaling (30 yr)

Gen1 (370x470mm)

Gen 8 (2200x2600 mm)

## ***Solar Panels***

Si Substrates

100 mm to 150 mm

2x scaling (20 yr)

Source: Brad Mattson, Sivapower  
D. Mitzi, Solution Processing of Inorganic Materials, 2010

# Summary

- Continuing advances in Si materials technology making
  - Microelectronics cheaper
  - Si PV reaching grid parity with fossil fuel electricity generation
- Manufacturing scale and growing demand for Si for PV further driving down the cost of polysilicon
- Further opportunities to improve materials utilization in Si PV

# Acknowledgements

- Graham Fisher, Mike Seacrist, Bob Standley, and a number of colleagues at MEMC Electronic Materials/SunEdison Semiconductor for discussions and for presentation material.